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# Statistical Reliability in Nanoscale Devices: The Bias Temperature Instability

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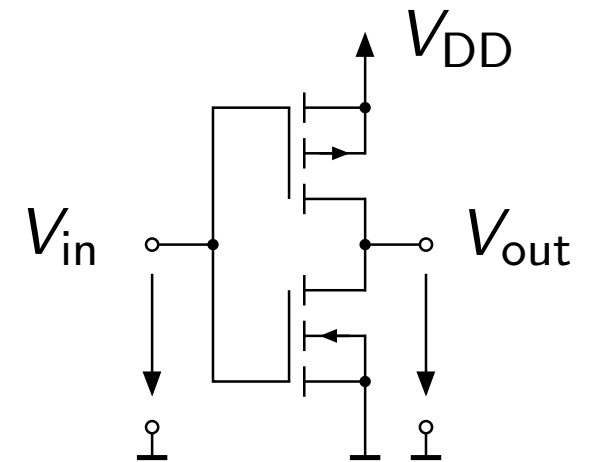
# The Negative Bias Temperature Instability

When does the NBTI scenario occur?

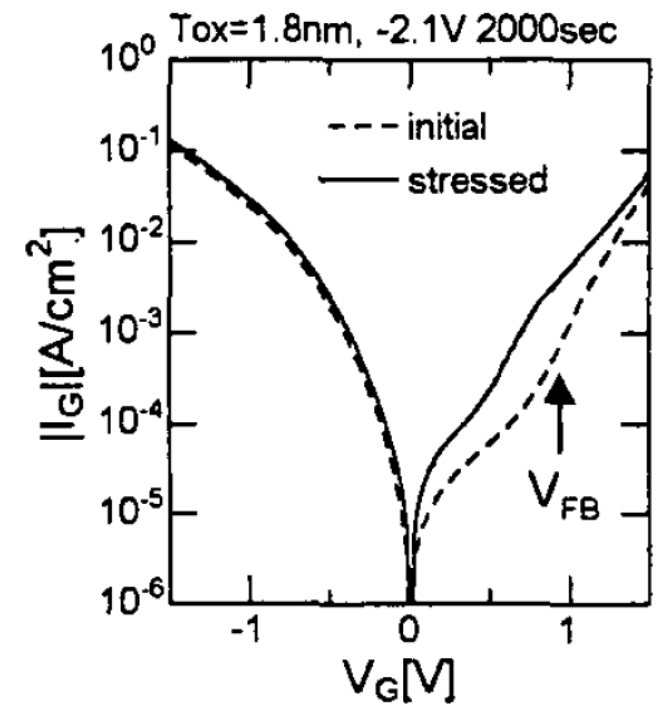
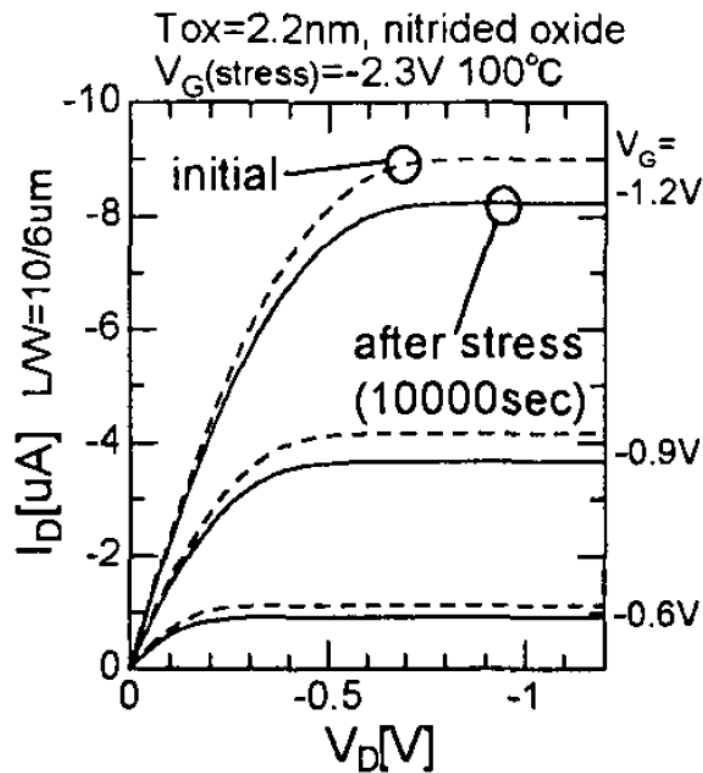
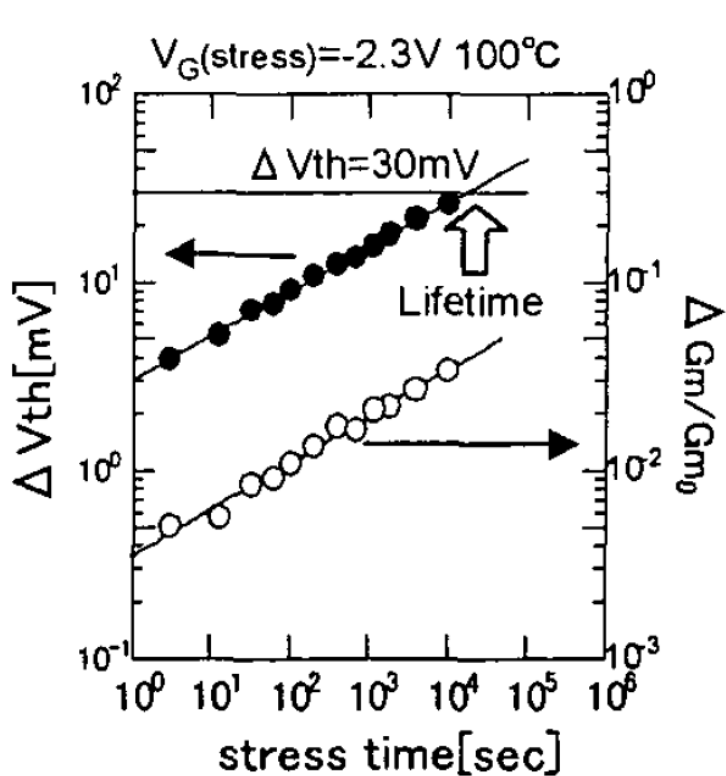
NBTI:  $V_G \ll 0V$ ,  $V_S = V_D = 0V$

Example: inverter with  $V_{in} = 0V$

Similar scenarios in ring-oscillators, SRAM cells, etc.



What happens to the pMOS transistor?



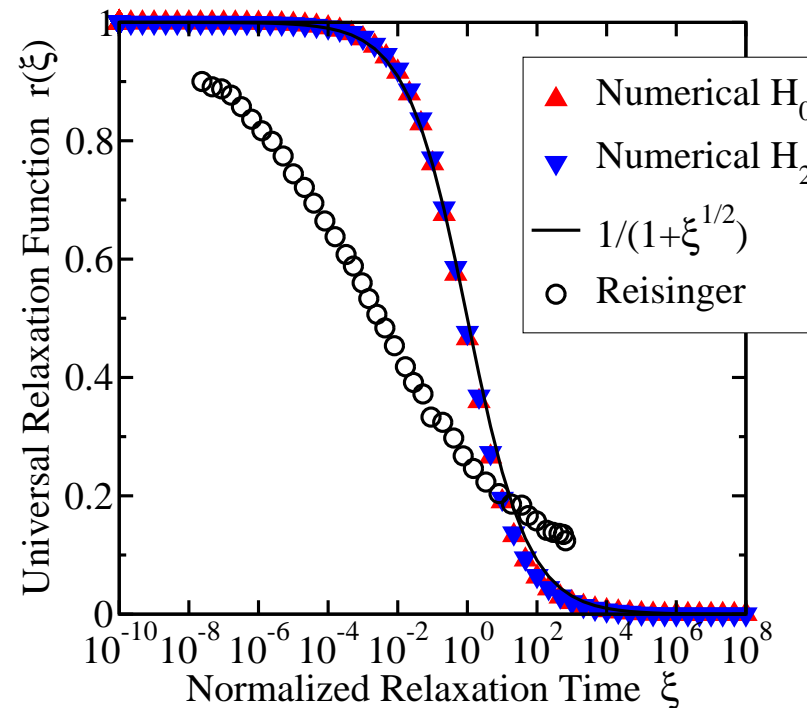
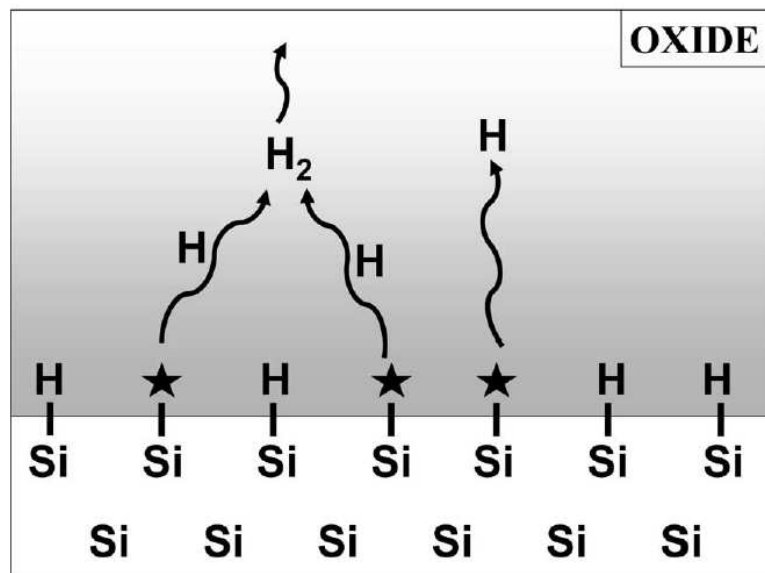
# Standard Model: Reaction-Diffusion Model

Successful in describing constant bias stress<sup>[1][2]</sup>

Cannot describe relaxation<sup>[3][4][5]</sup>

Relaxation sets in too late and is then too fast, bias independent

Wrong duty-factor dependence in AC stress: 80% (theory) vs. 50% (measured)



**Model is wrong!!!** <sup>[6][7][8][9][10]</sup>

[1] Jeppson and Svensson, JAP '77 [2] Alam *et al.*, MR '06 [3] Kaczer *et al.*, IRPS '05 [4] Grasser *et al.*, IRPS '07

[5] Huard *et al.*, IEDM '07 [6] Grasser *et al.*, IEDM '10 [7] Grasser *et al.*, IRPS '10 [8] Reisinger *et al.*, IRPS '10

[9] Kaczer *et al.*, IRPS '10 [10] Huard *et al.*, IRPS '10

# Overview

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## Introduction

Stochastic NBTI on small-area devices: link NBTI and RTN

## New measurement technique

The time dependent defect spectroscopy

## Anomalous defect behavior

Present in all defects

## Stochastic model

Additional metastable states, multiphonon theory

## Implications

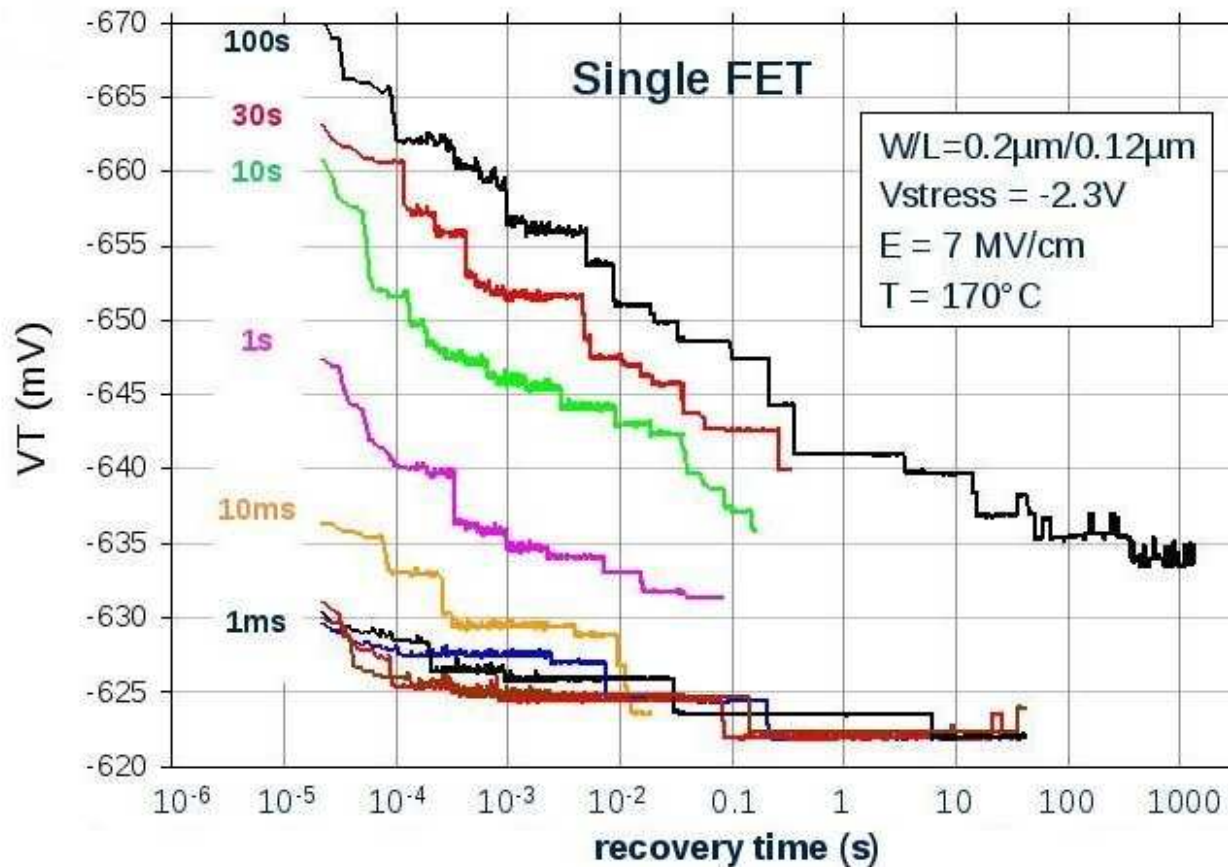
Lifetime of nanoscale MOSFETs

## Conclusions

# What is Really Going On?

Study of NBTI recovery on small-area devices [1] [2] [3] [4] [5]

Stochastic and discrete charge emission events, no diffusion



[1] Reisinger *et al.*, IIRW '09 [2] Grasser *et al.*, IEDM '09 [3] Kaczer *et al.*, IRPS '10 [4] Grasser *et al.*, IRPS '10

[5] Reisinger *et al.*, IRPS '10

# Recoverable NBTI due to the same Defects as RTN

## Quasi-equilibrium:

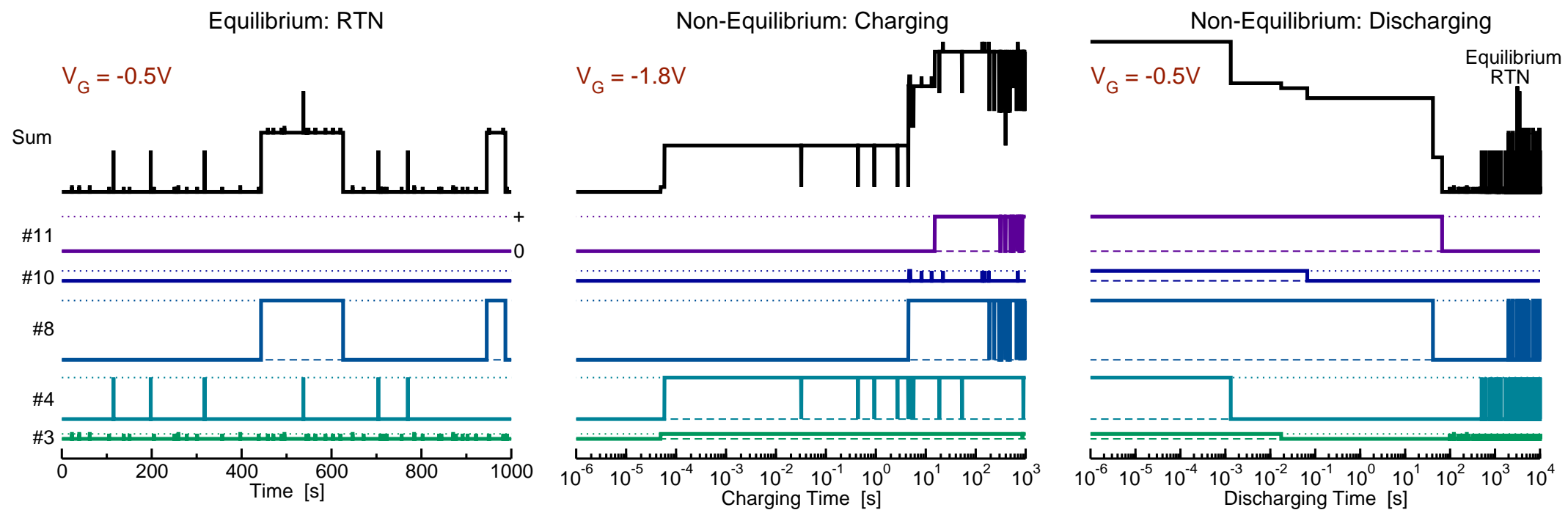
Some defects neutral, others positive, a few produce random telegraph noise (RTN)

## Stress:

Defects switch to new equilibrium (mostly positive), a few may produce RTN

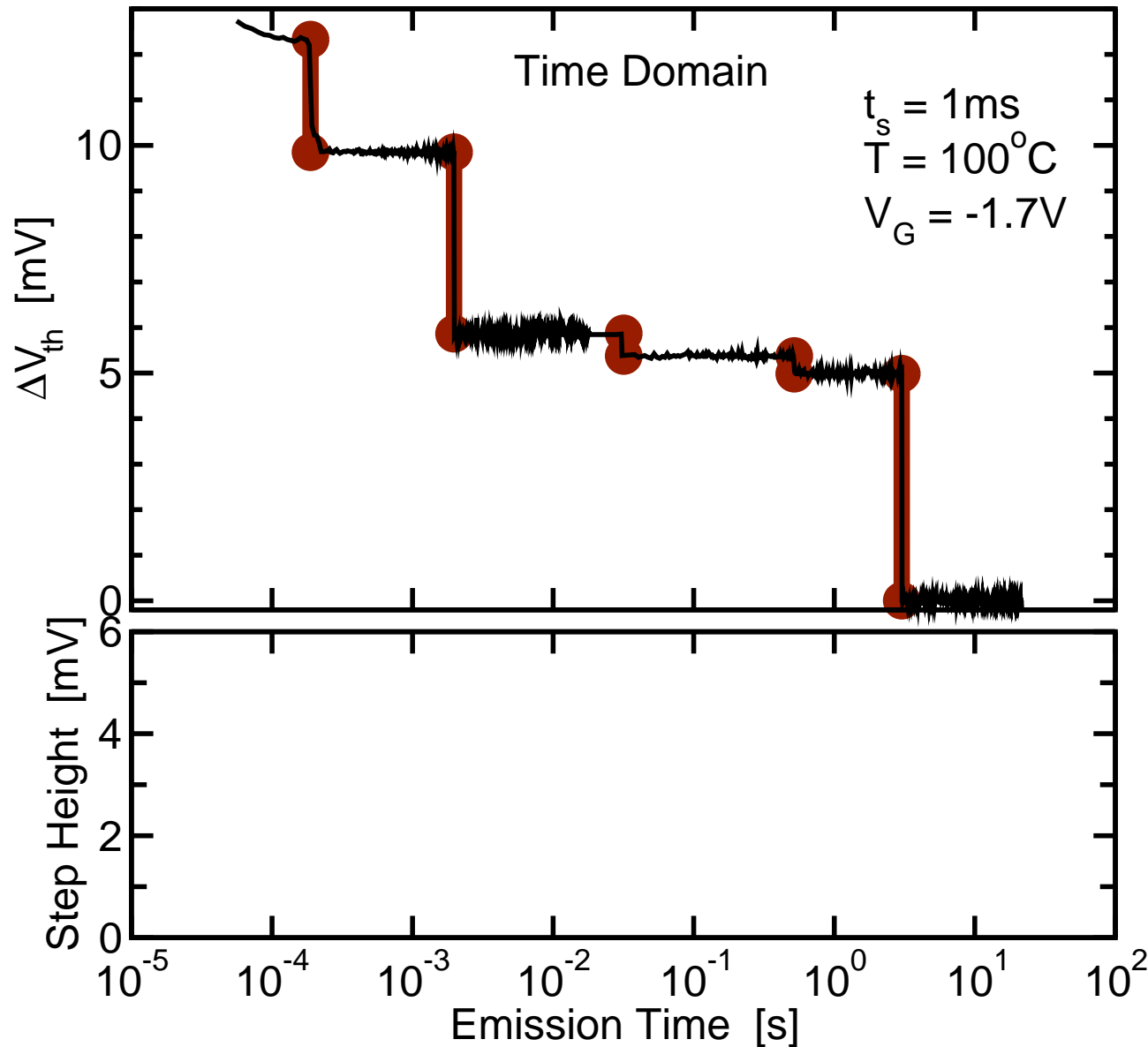
## Recovery:

Slow transition (broad distribution of timescales) to initial quasi-equilibrium



# The Time Dependent Defect Spectroscopy (TDDS) .....

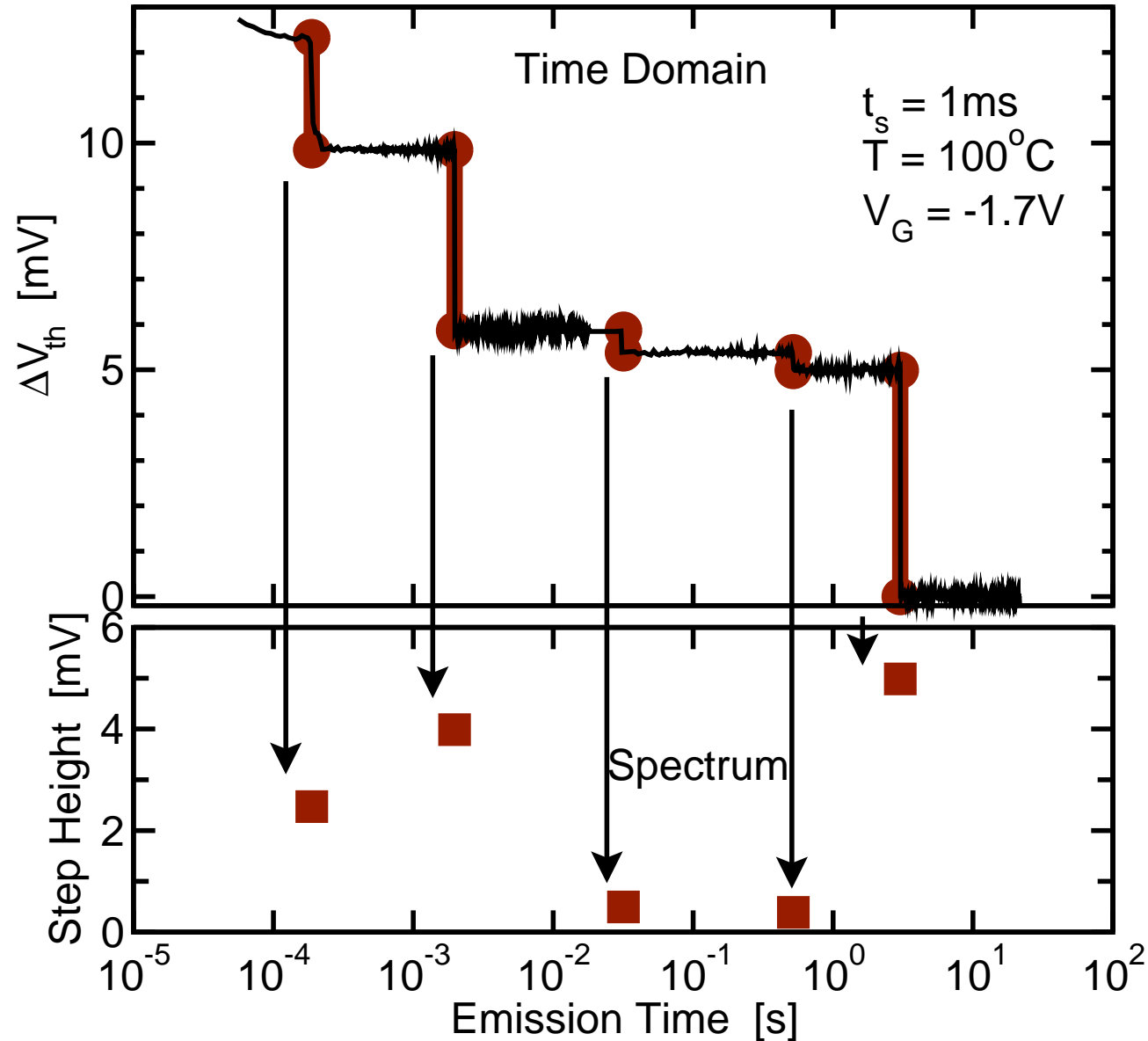
Analyzes contributions from multiple traps via **spectral maps** [1][2]



[1] Grasser *et al.*, IRPS '10 [2] For a discussion on the step heights see Kaczer *et al.*, IRPS '10

# The Time Dependent Defect Spectroscopy (TDDS) .....

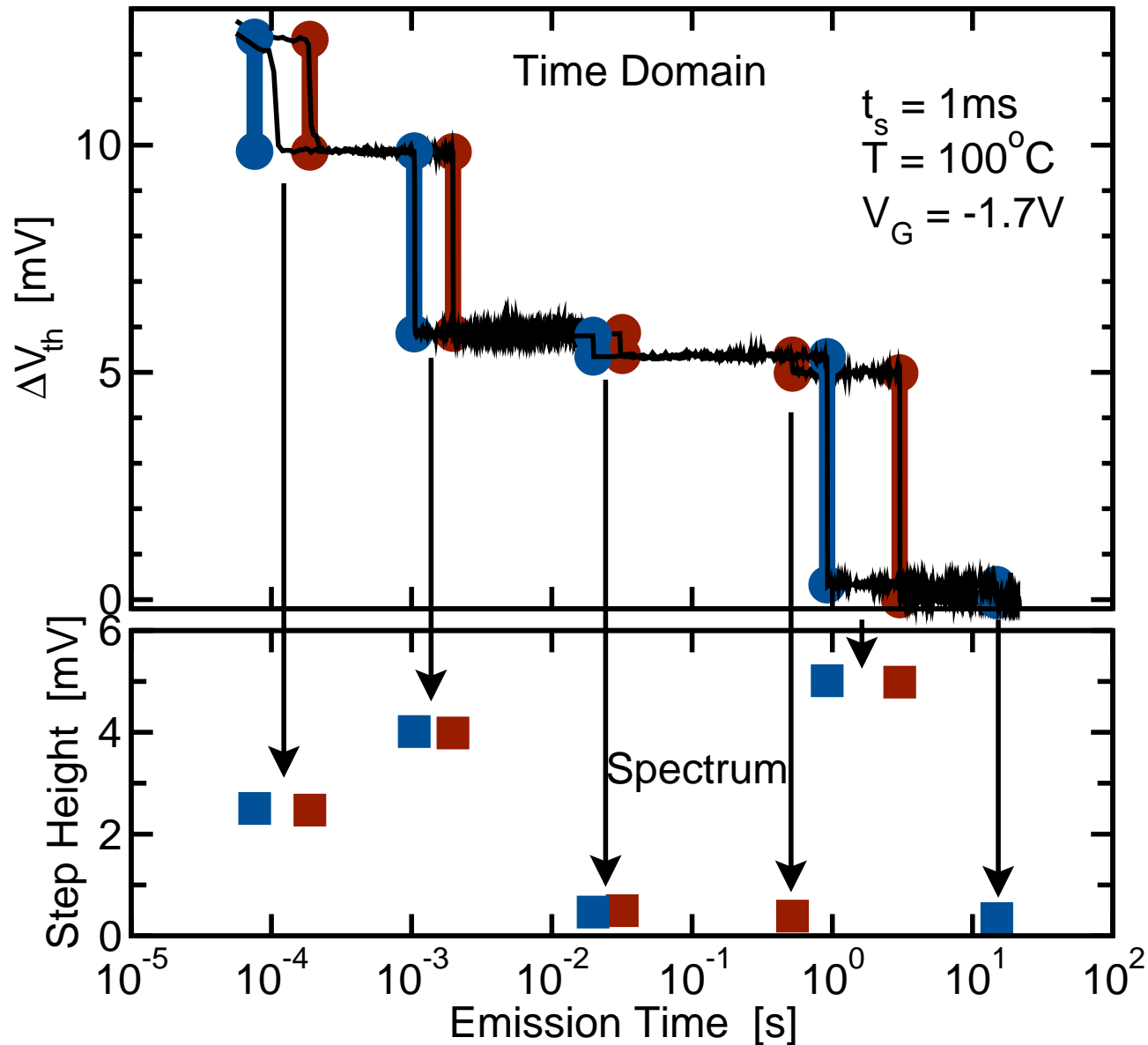
Analyzes contributions from multiple traps via **spectral maps**





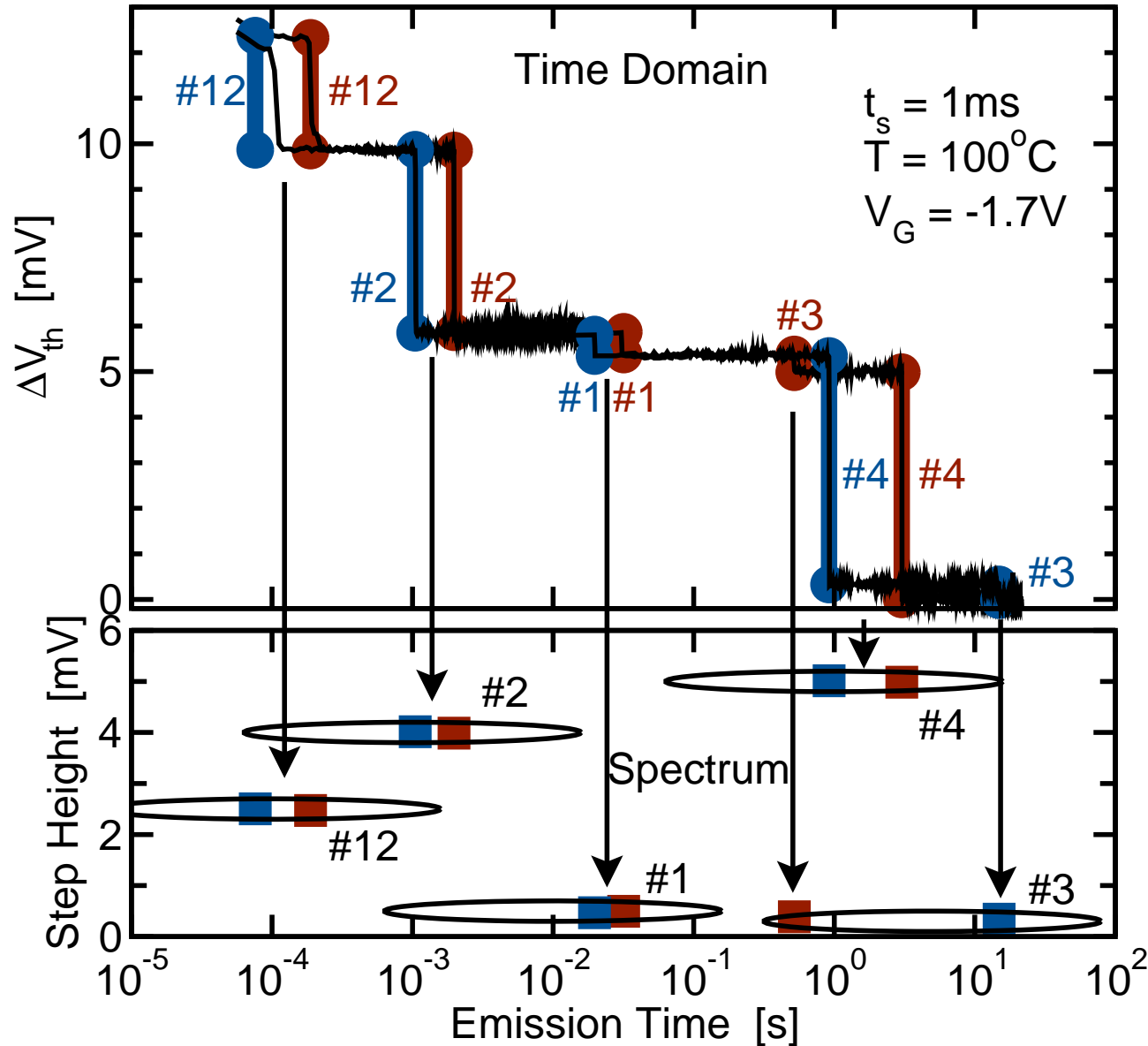
# The Time Dependent Defect Spectroscopy (TDDS) .....

Analyzes contributions from multiple traps via **spectral maps**



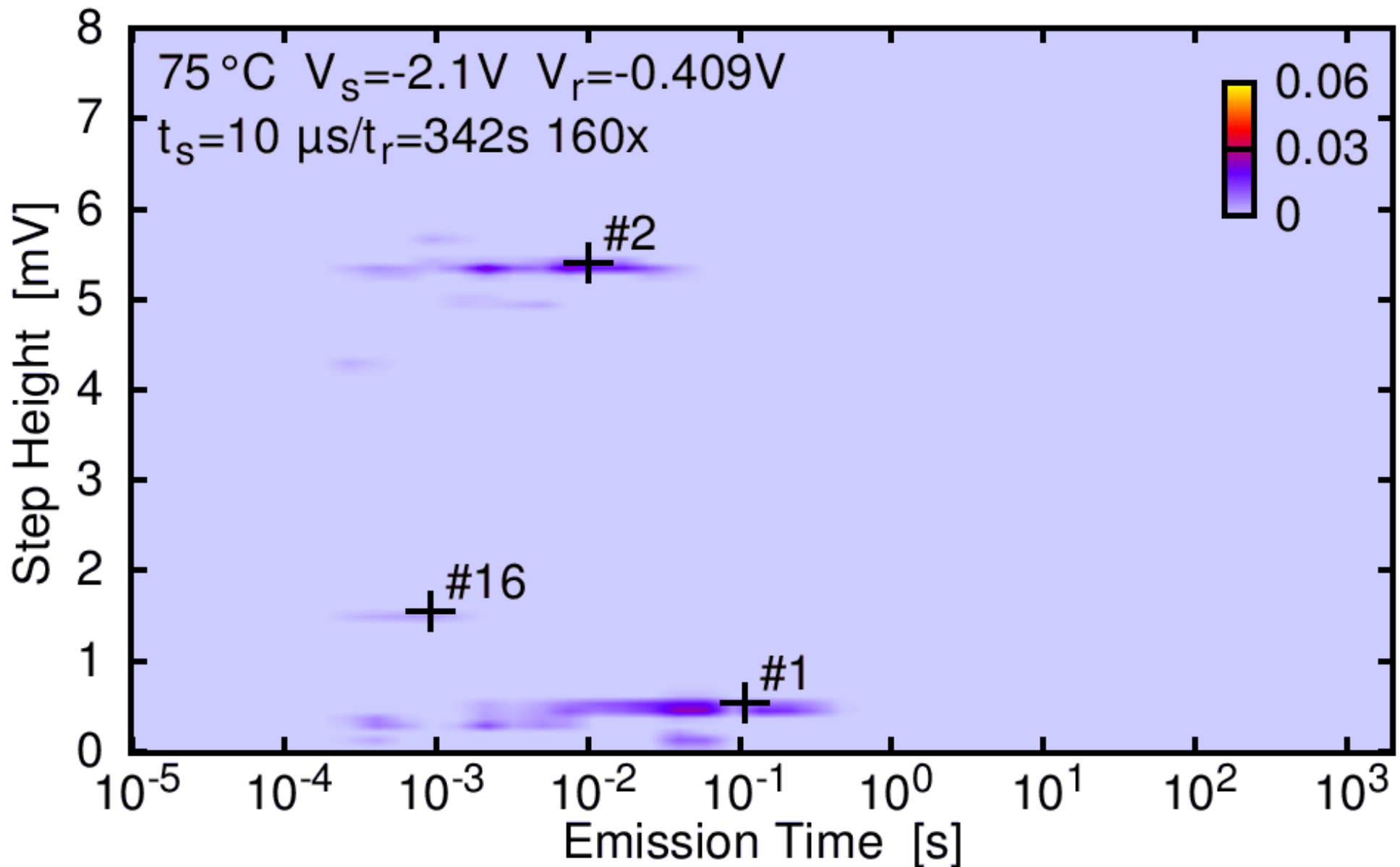
# The Time Dependent Defect Spectroscopy (TDDS) .....

Analyzes contributions from multiple traps via **spectral maps**



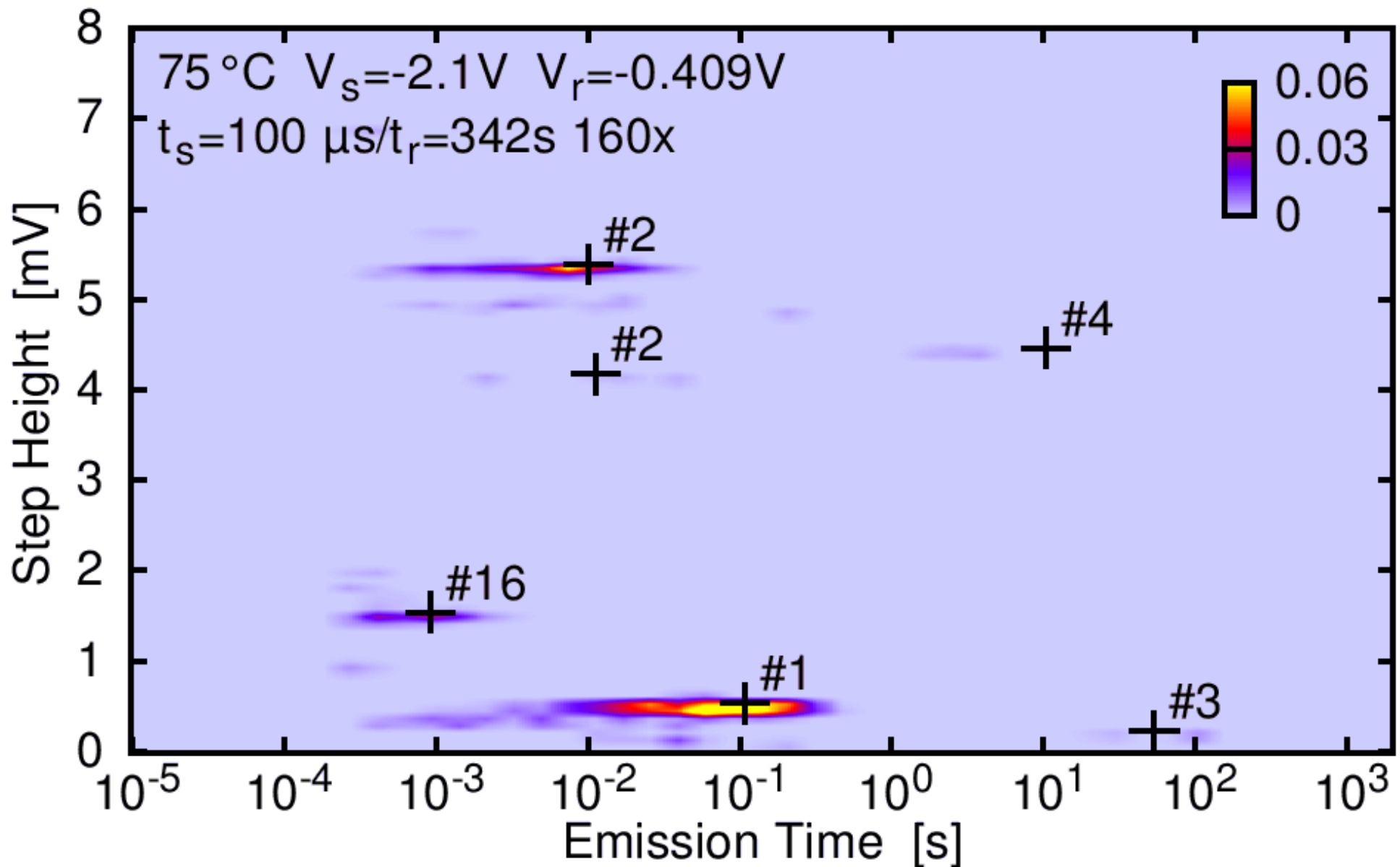
# The Time Dependent Defect Spectroscopy

Function of stress time  $t_s$



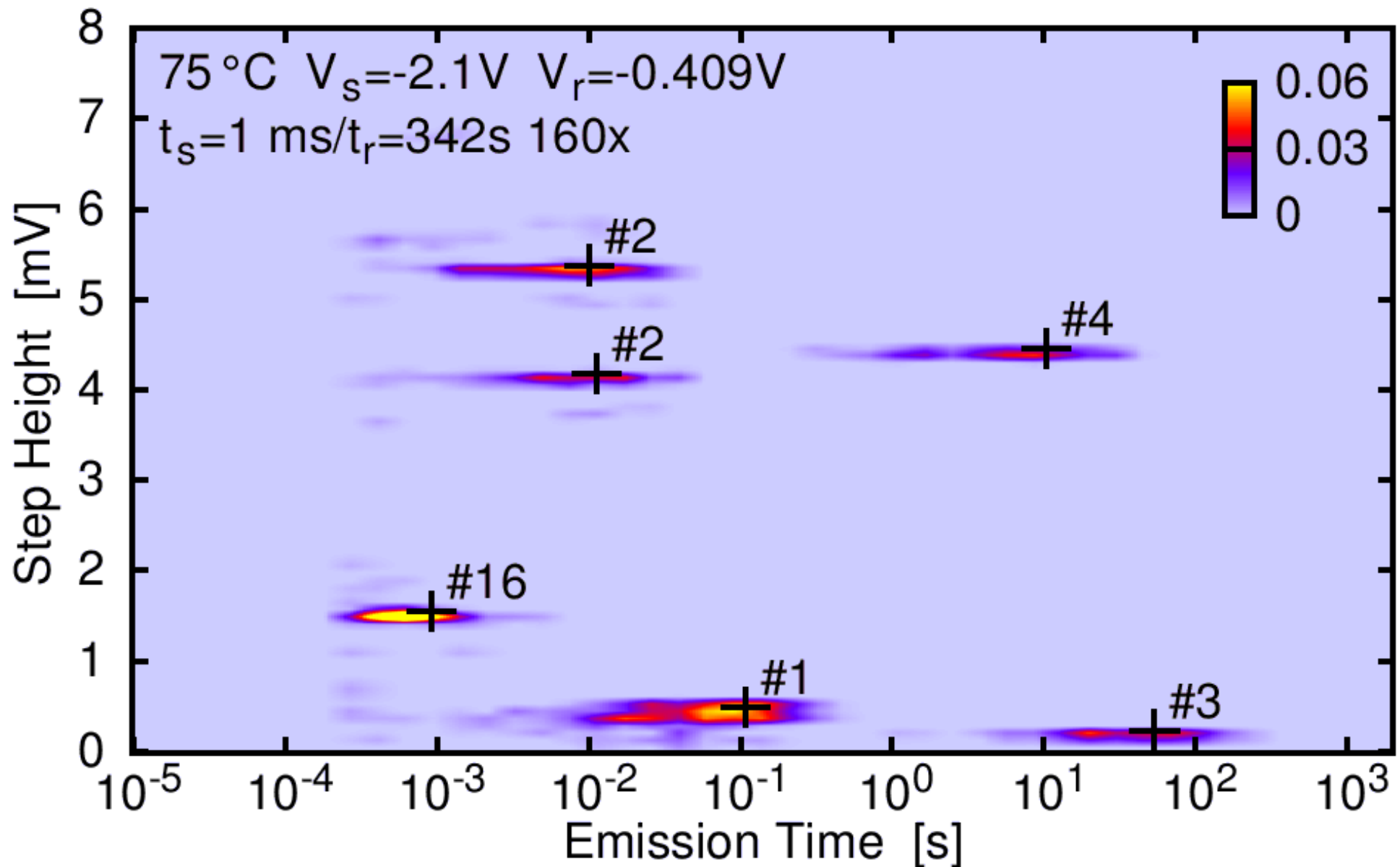
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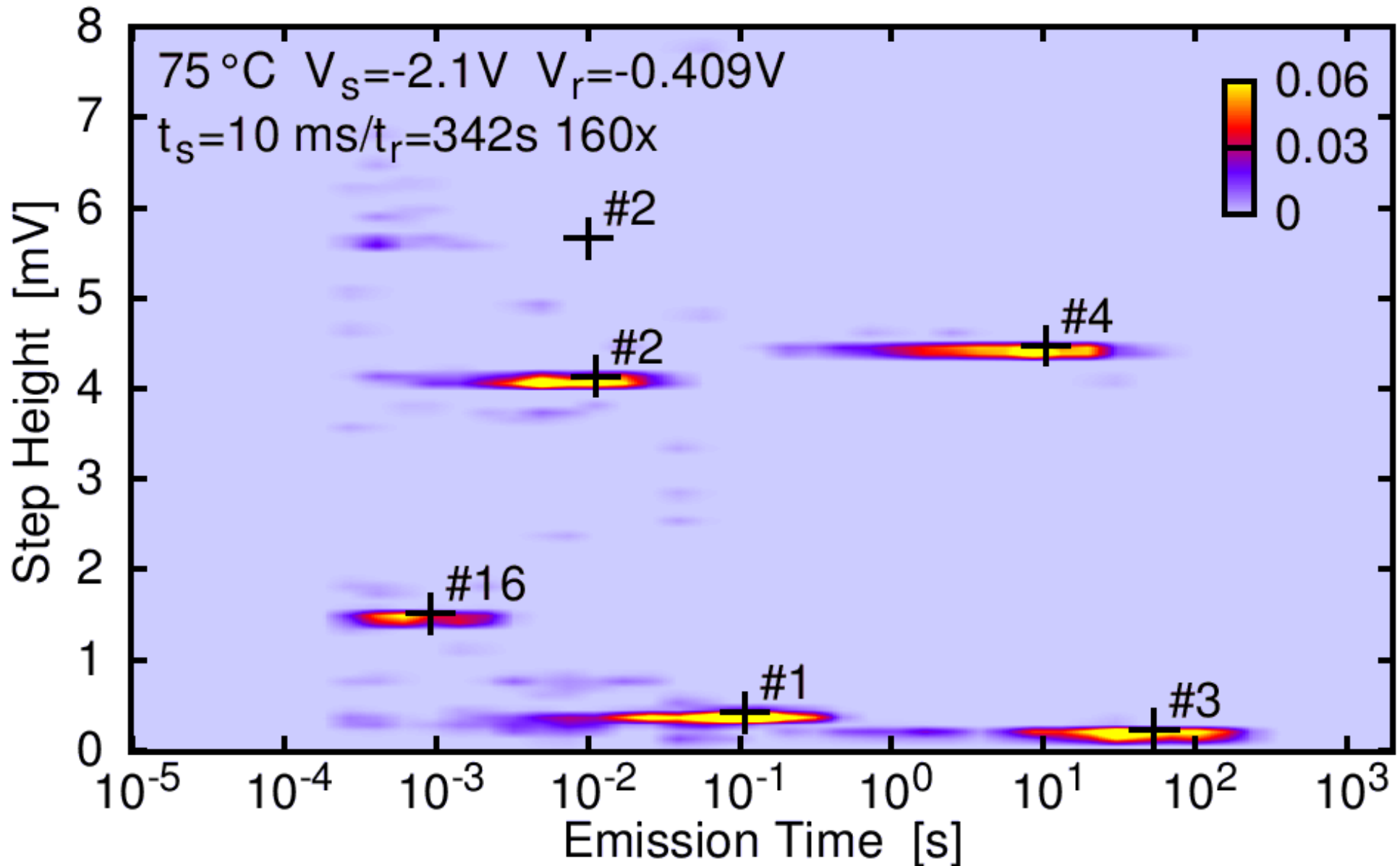
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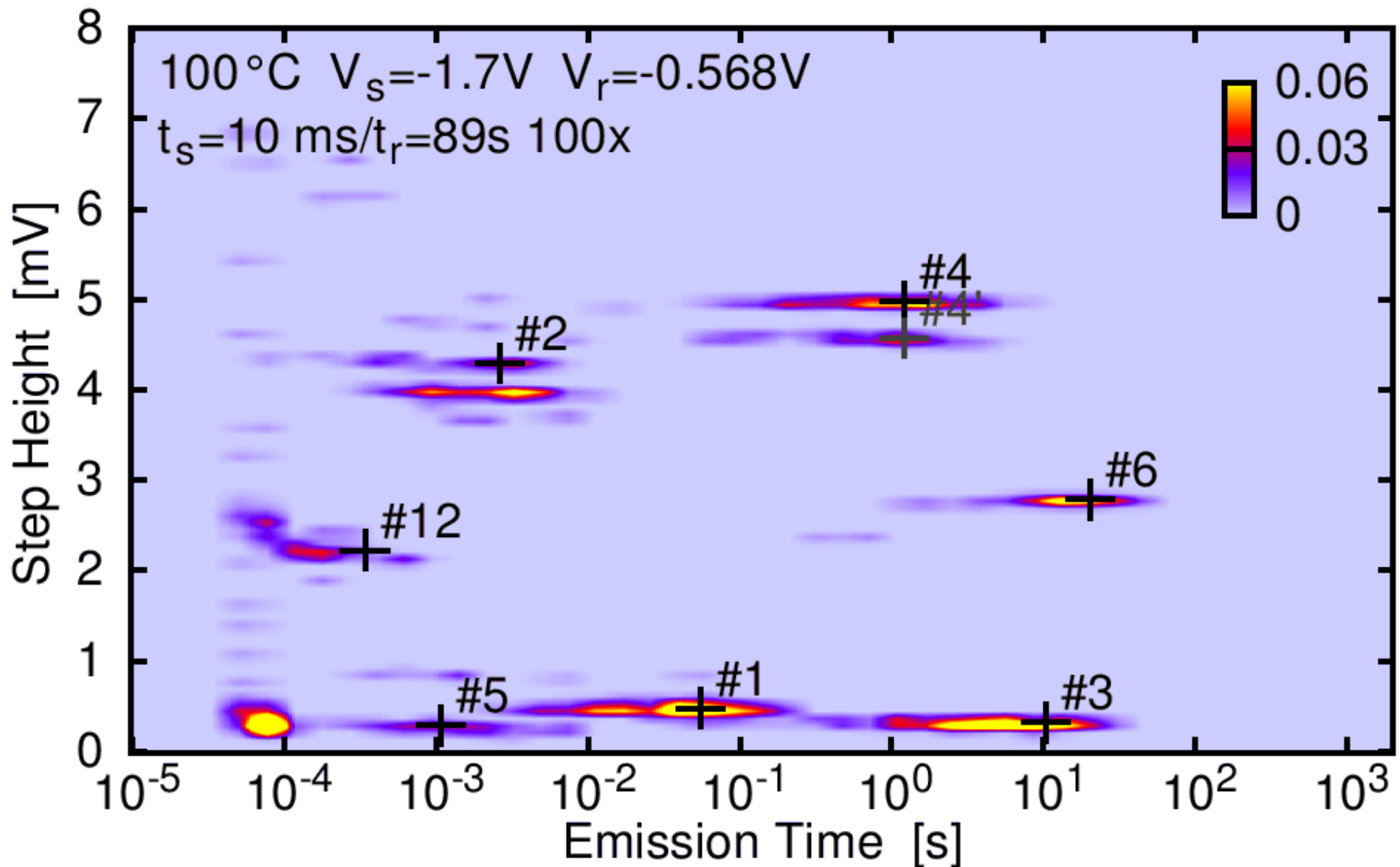
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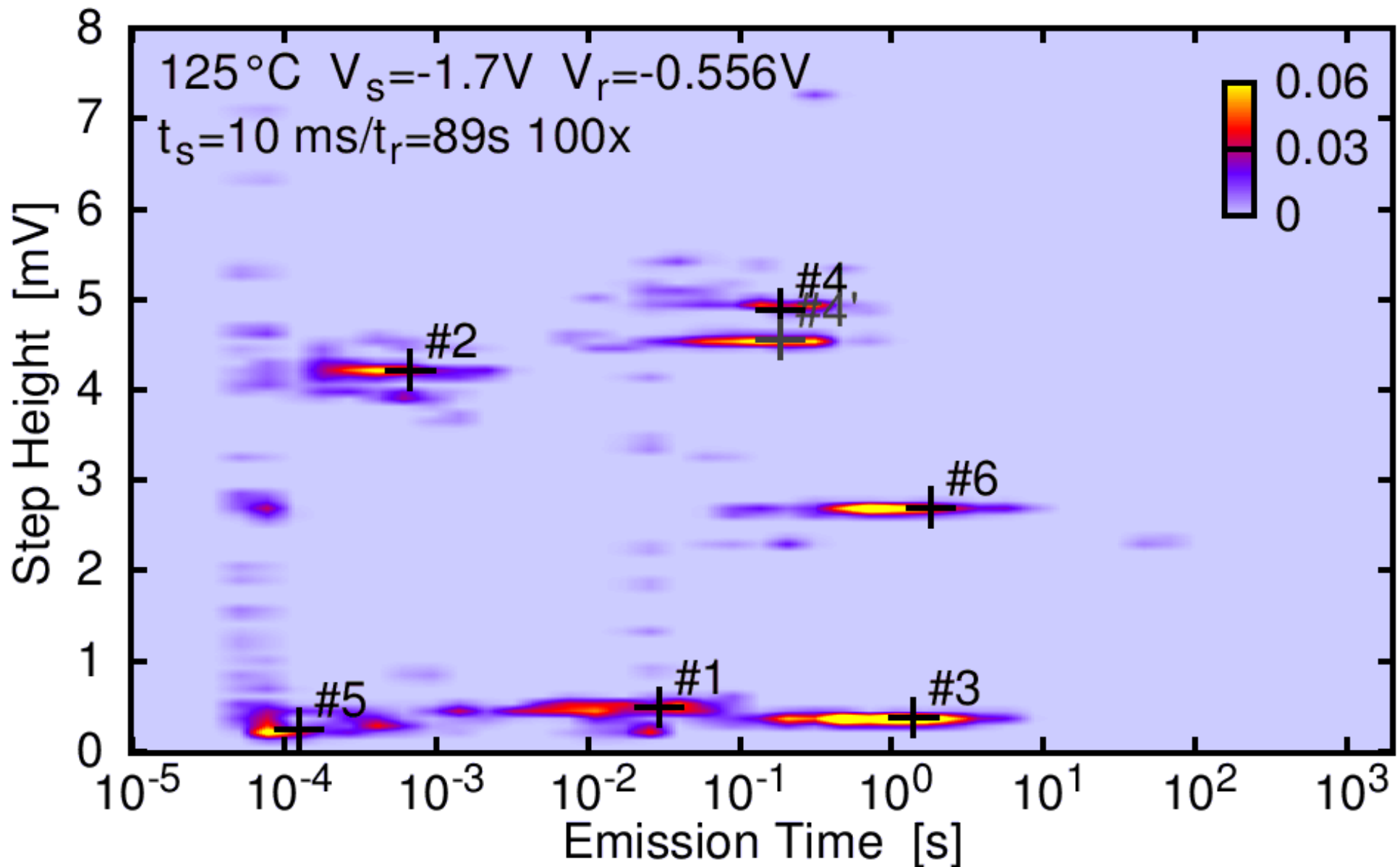
# The Time Dependent Defect Spectroscopy

Function of temperature



# The Time Dependent Defect Spectroscopy

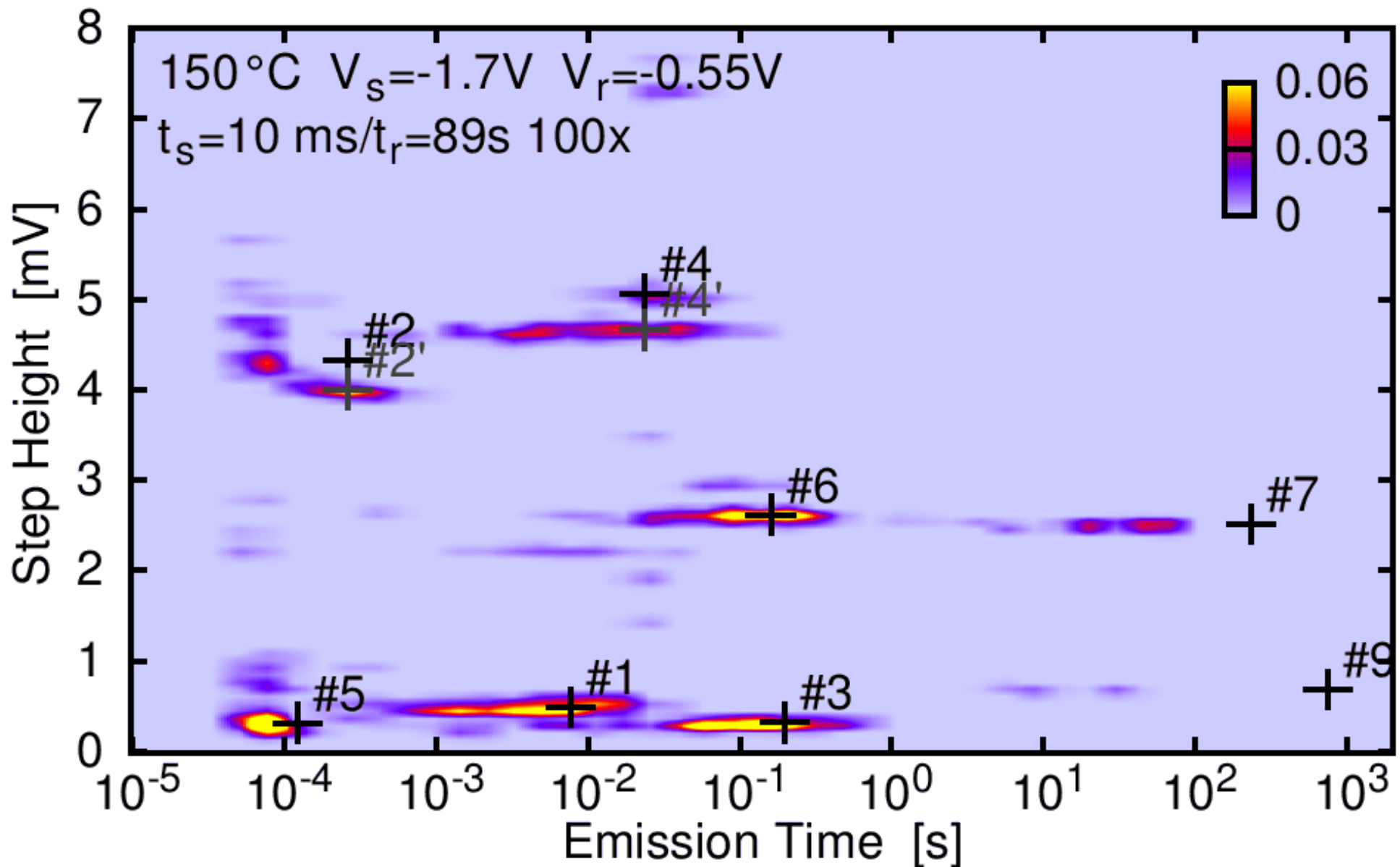
Function of temperature





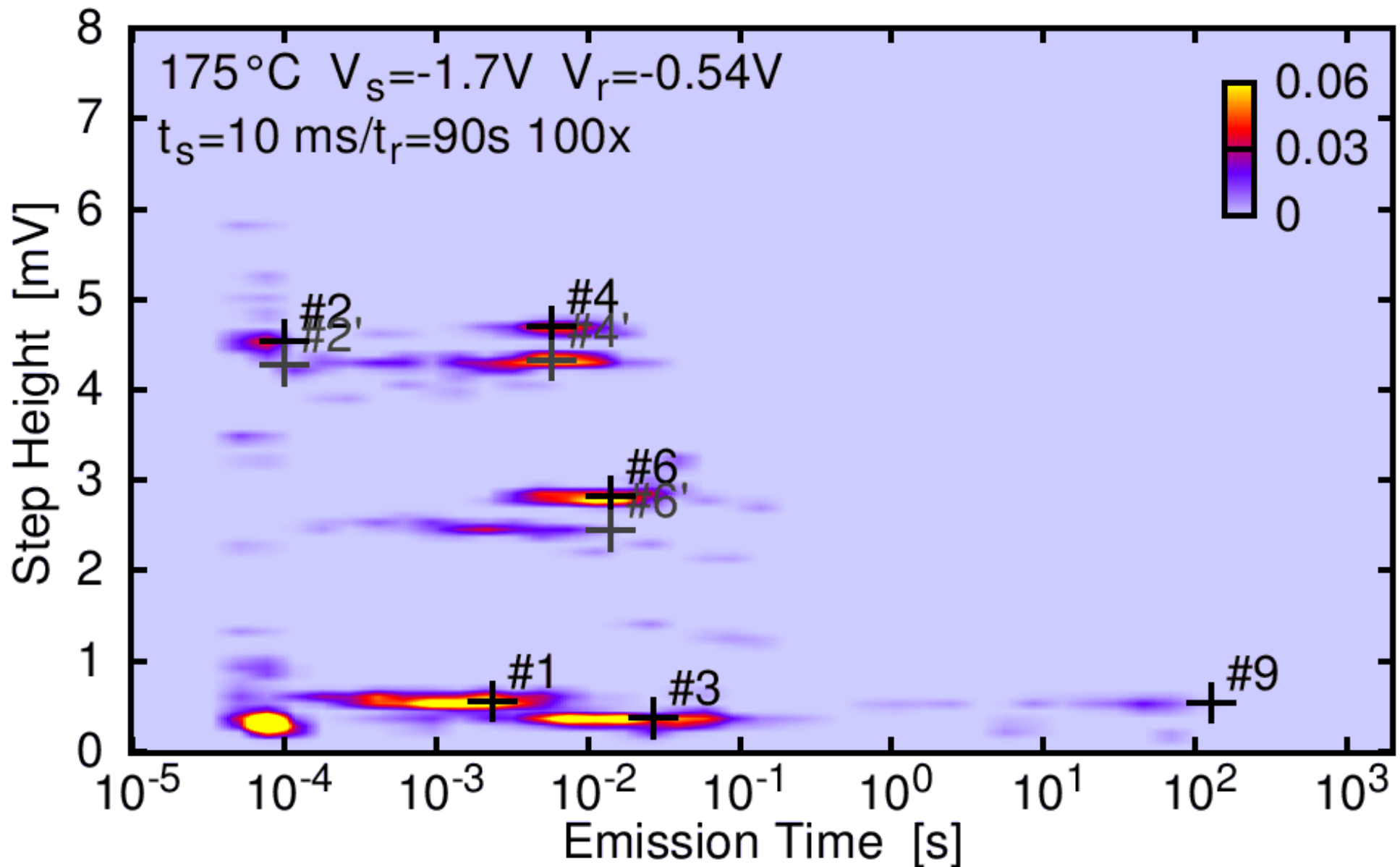
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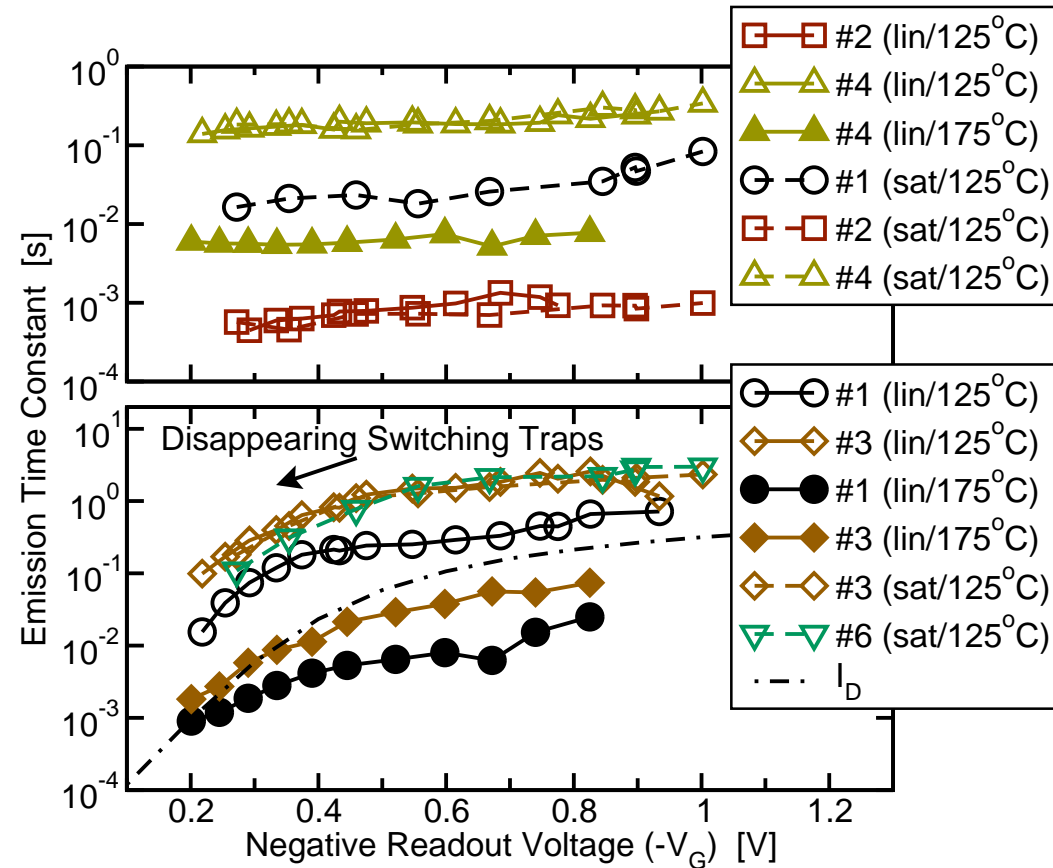
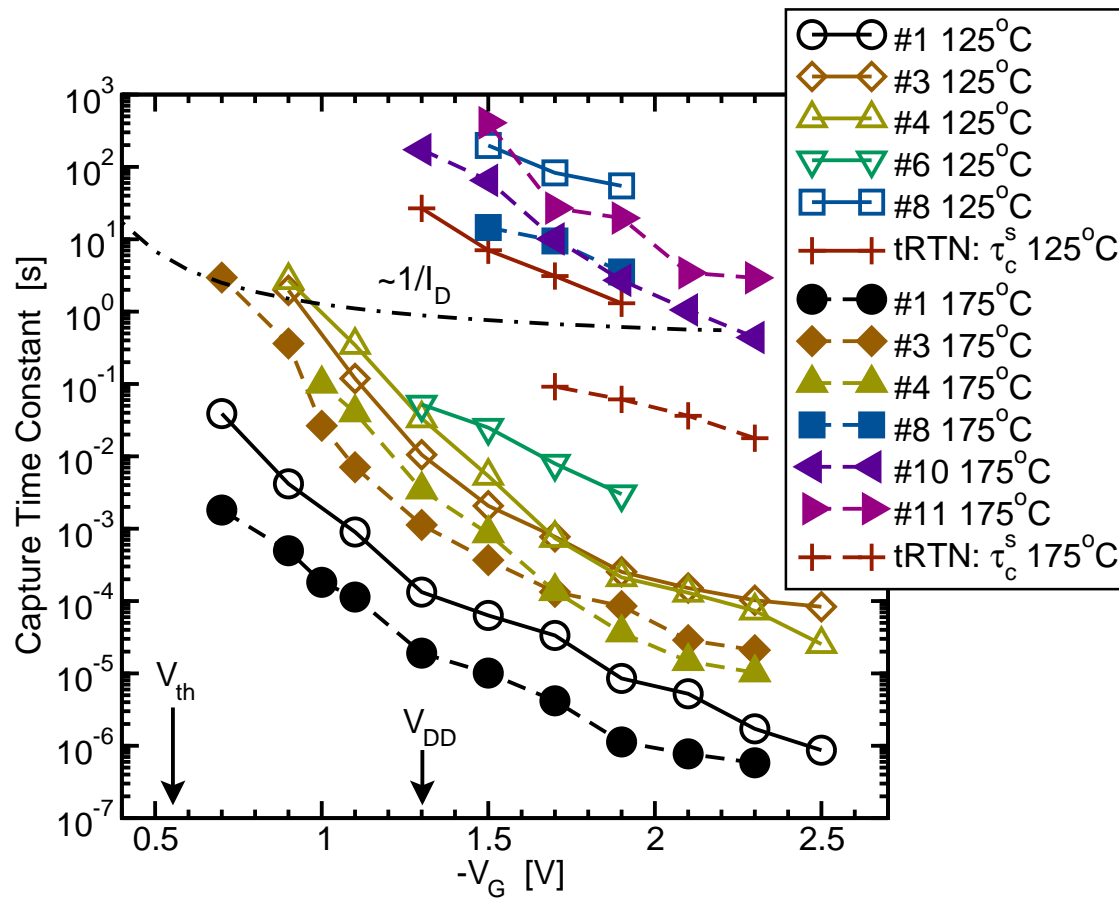
Function of temperature



# The Time Dependent Defect Spectroscopy

Different non-linear field dependence of the capture time constants

Different bias dependence of emission time constant: two defect types?

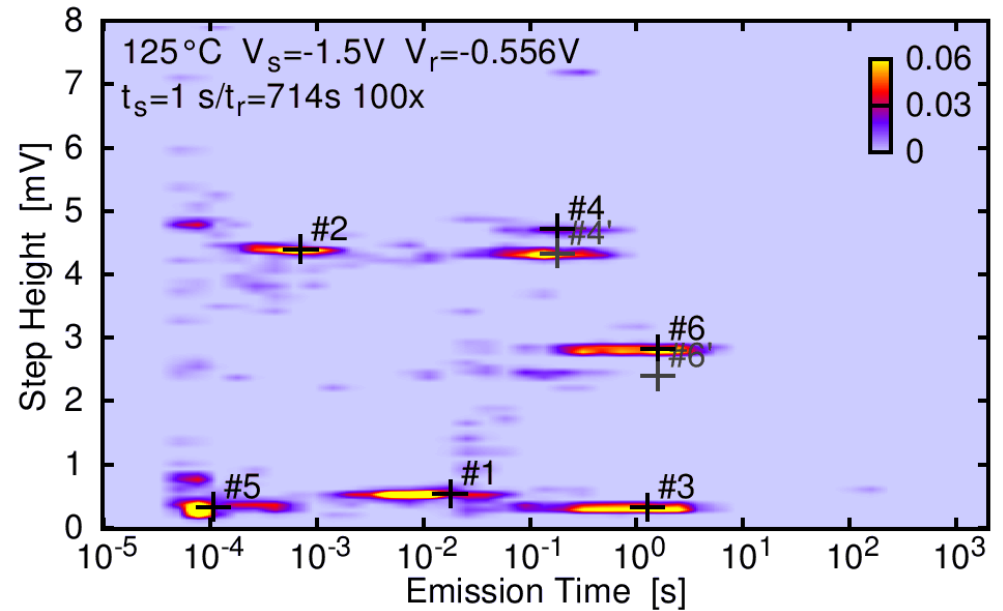
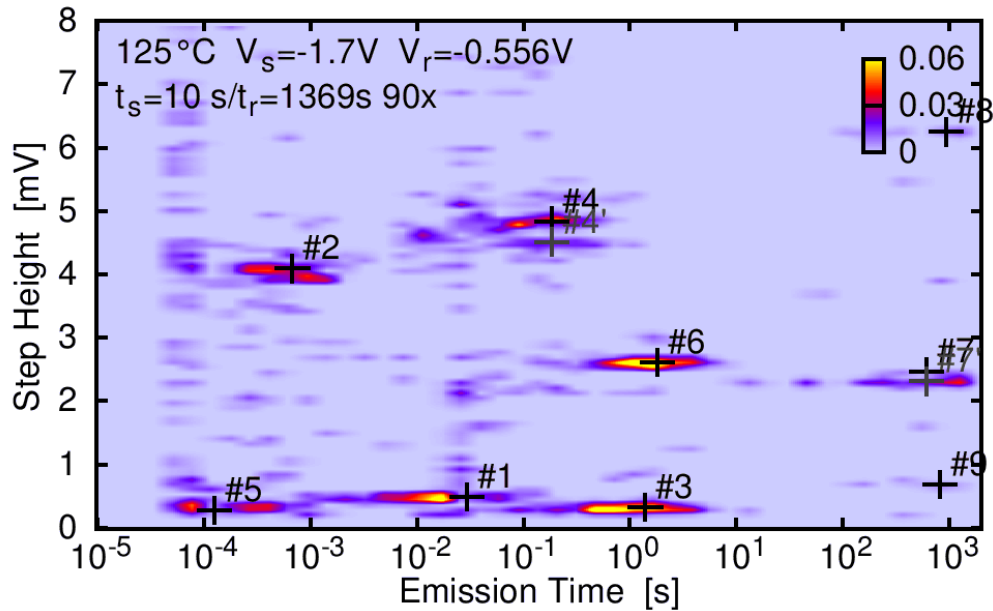


Compare SRH-like model:  $\tau_c = \tau_0 e^{\beta \Delta E_B} \frac{N_V}{p}$

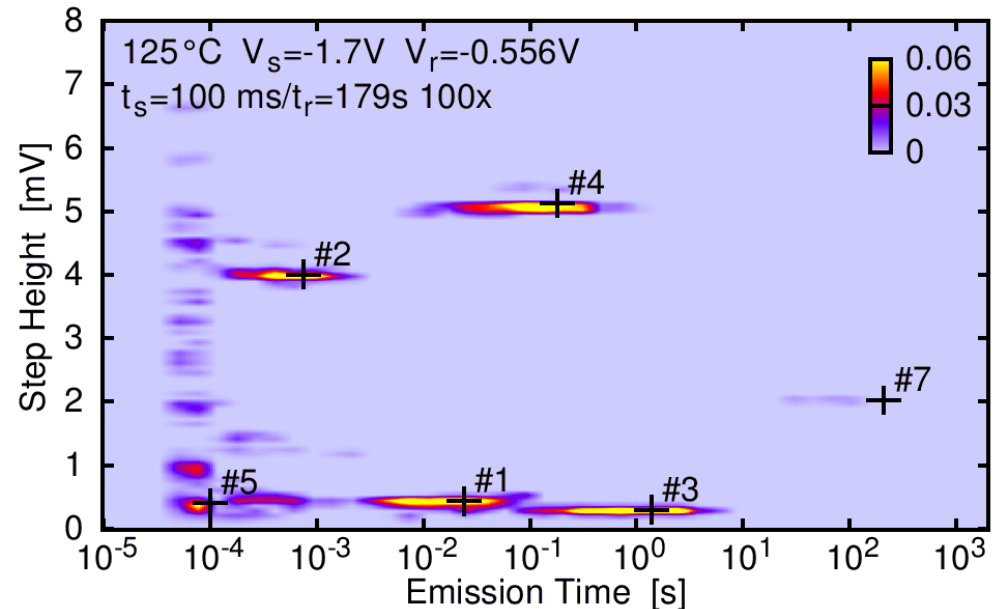
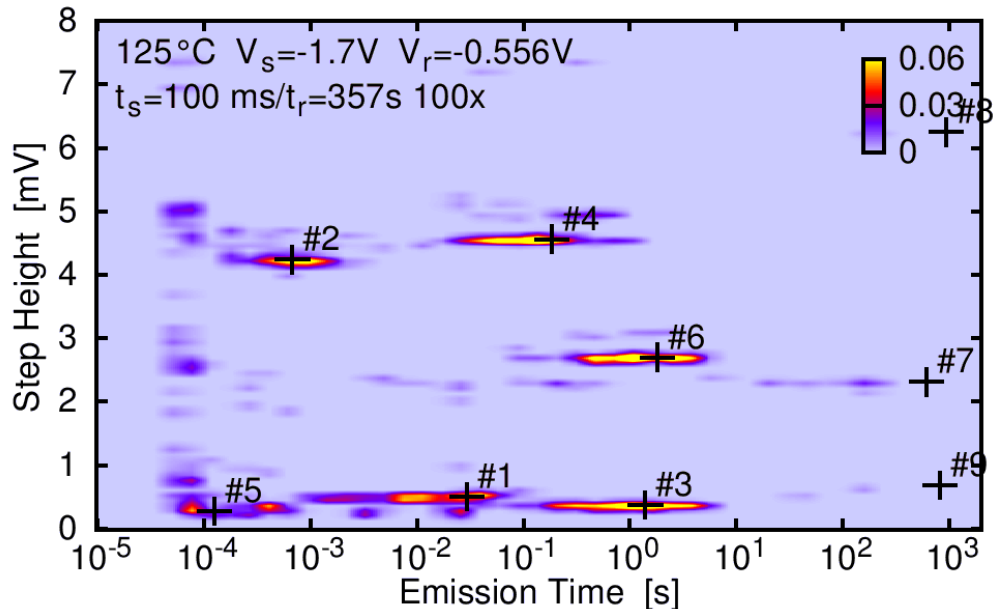
$$\tau_e = \tau_0 e^{\beta \Delta E_B} e^{\beta \Delta E_T} e^{x F / V_T}$$

# Anomalous Defect Behavior

Defects disappear temporarily from the map (#7)

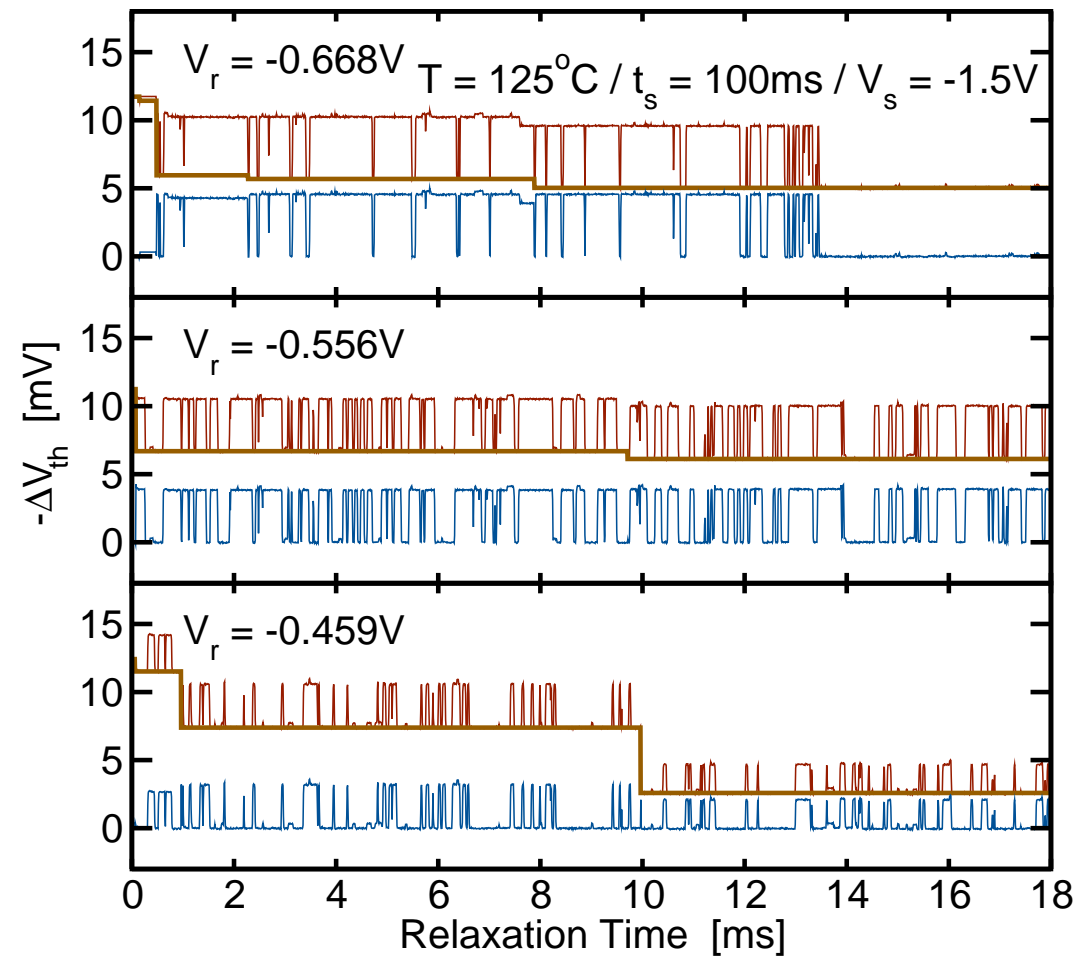
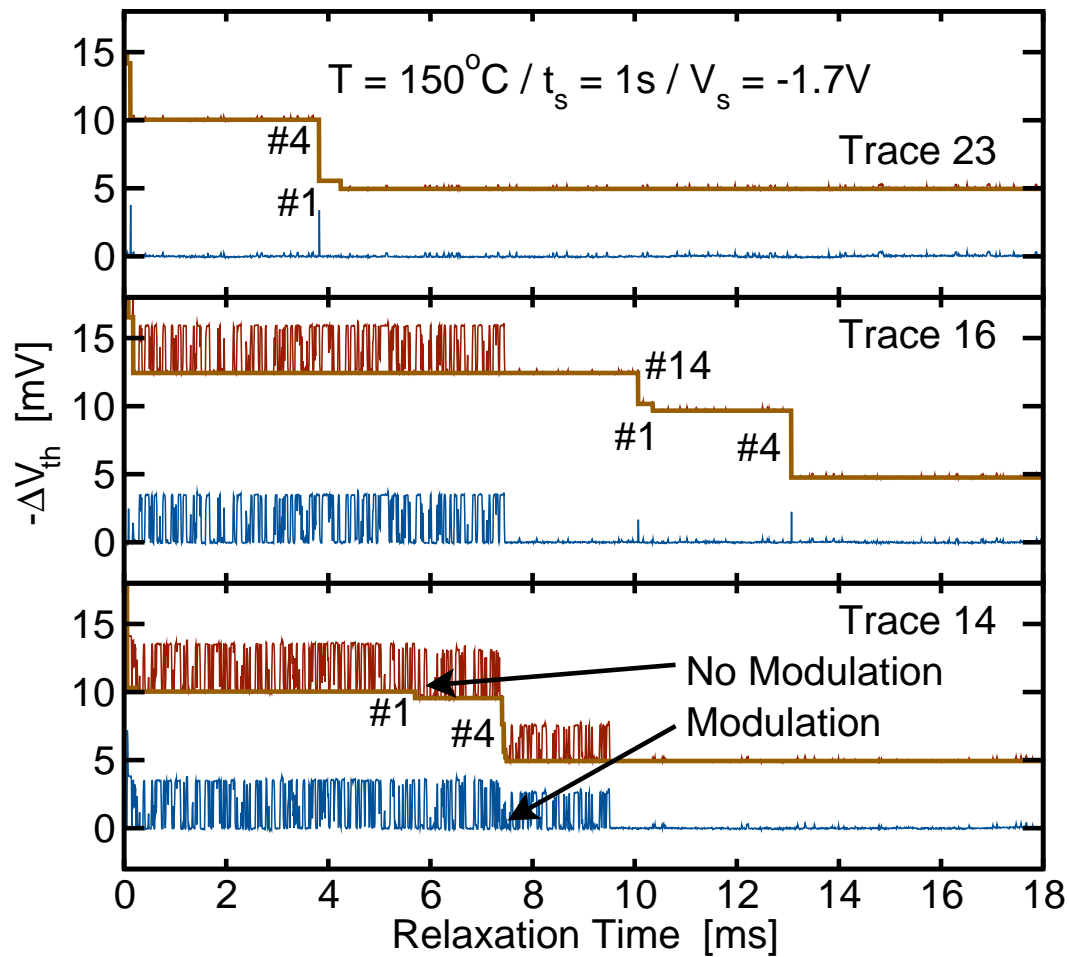


Long term stability: defect #6 missing for a few months now



# Anomalous Defect Behavior

## Temporary random telegraph noise (tRTN)

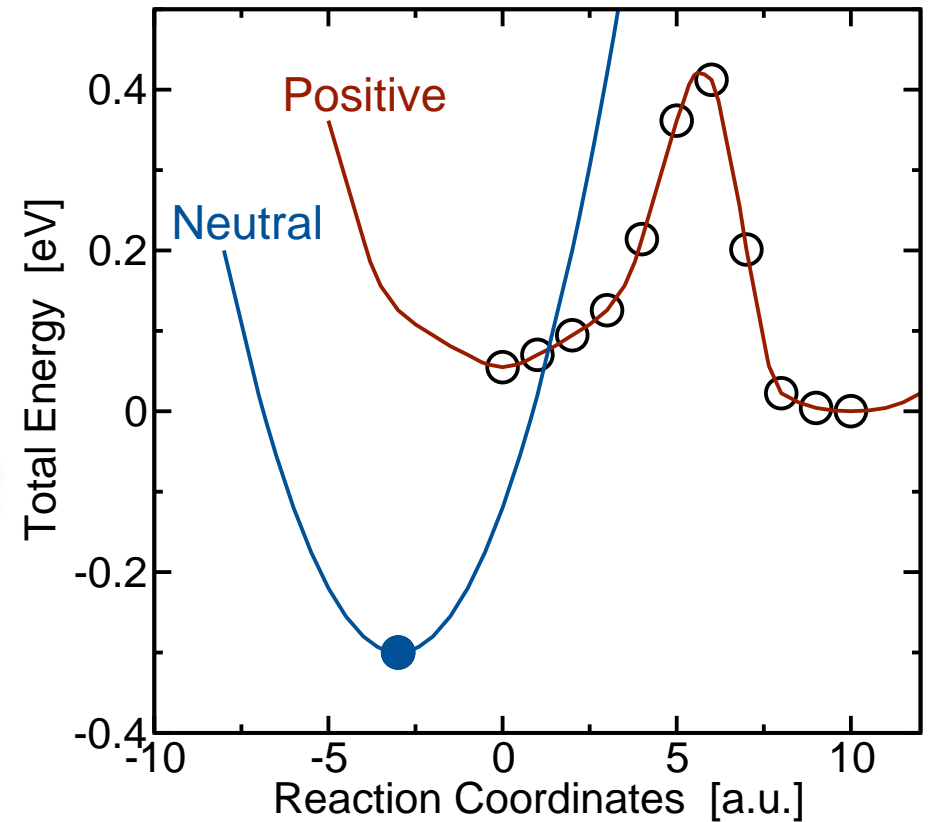
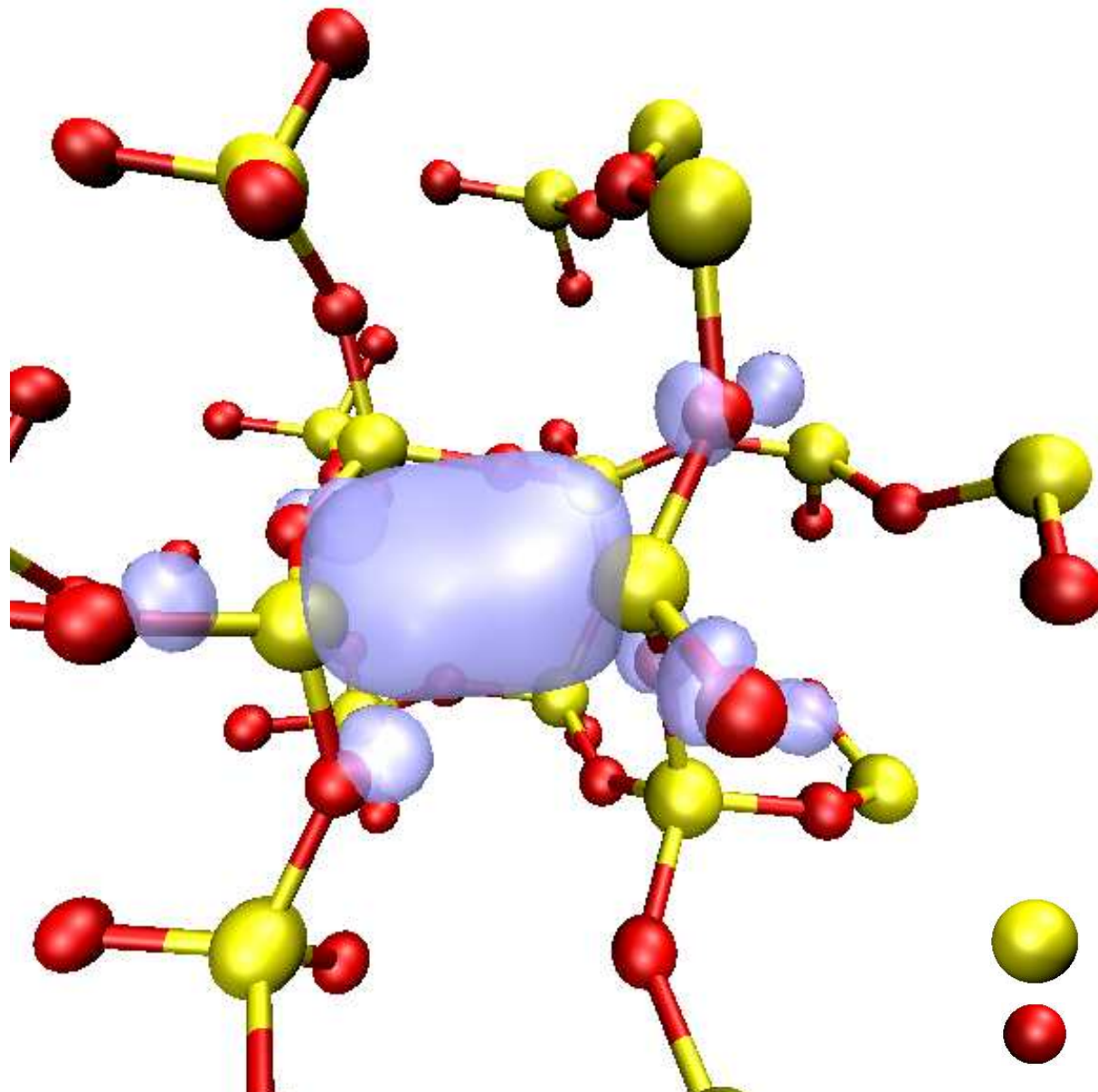


# How Can We Model All That?



# Lattice Relaxation and Metastability

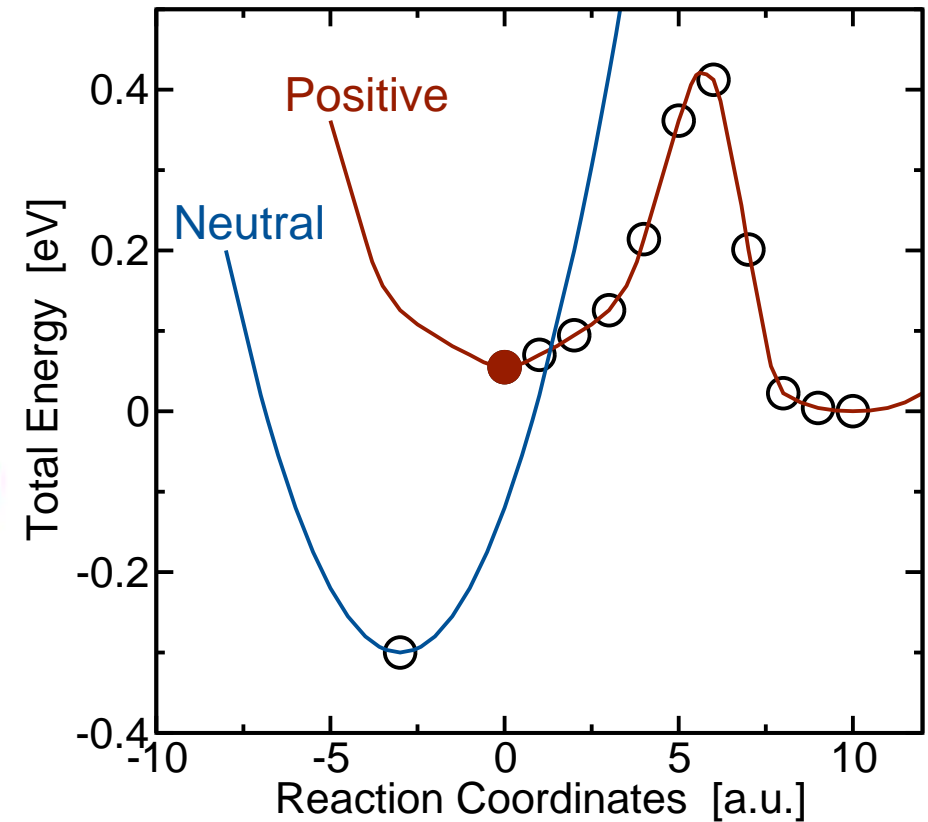
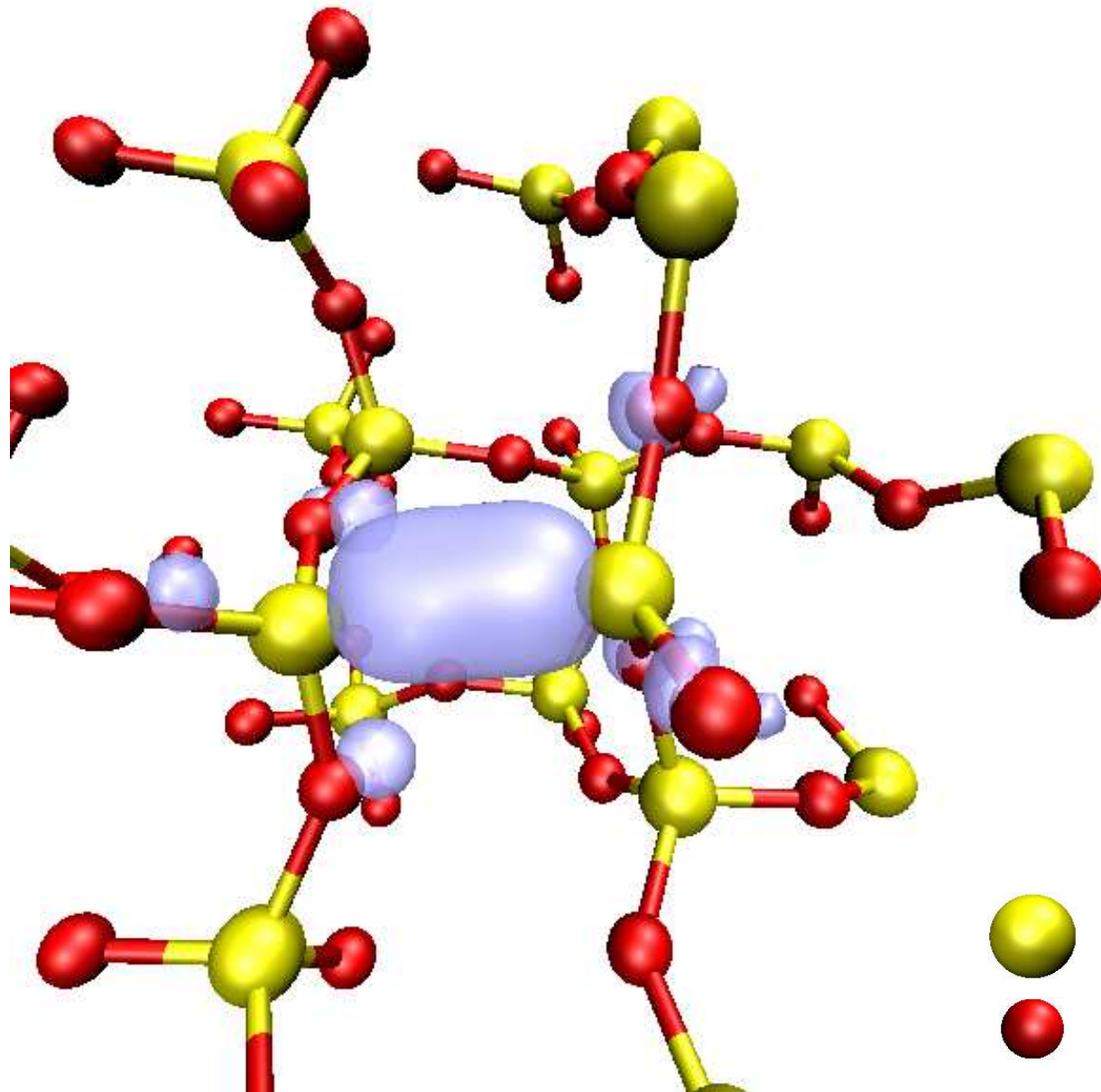
Density functional calculations (DFT) of  $E'$  center 'charging & puckering'



- Silicon
- Oxygen

# Lattice Relaxation and Metastability

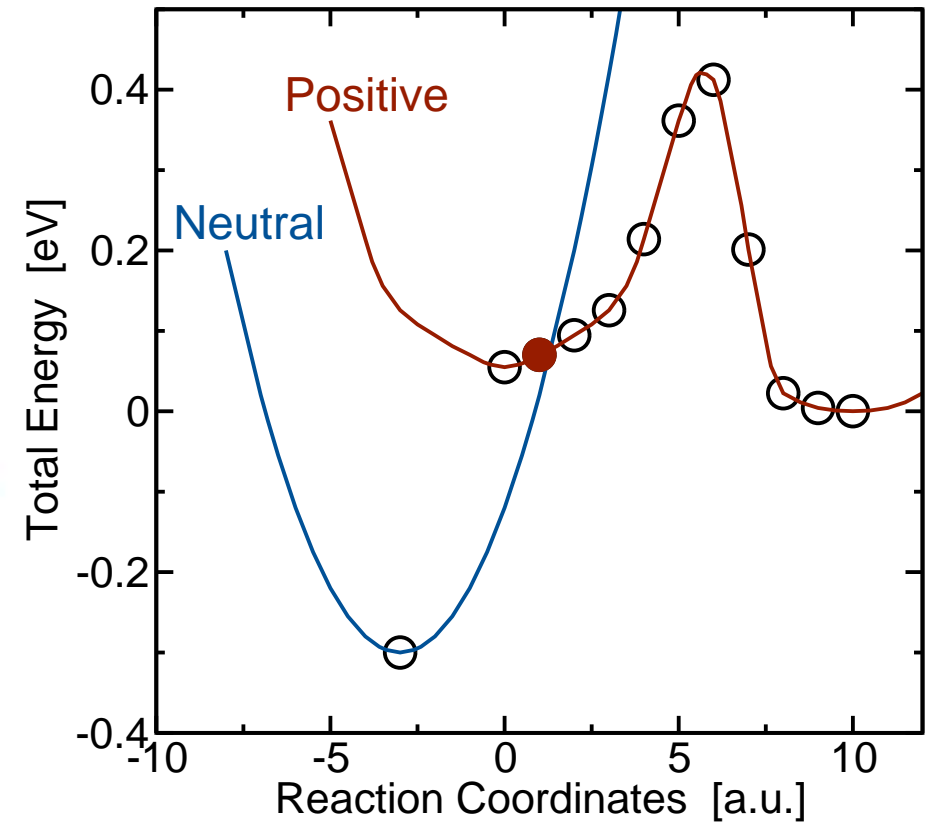
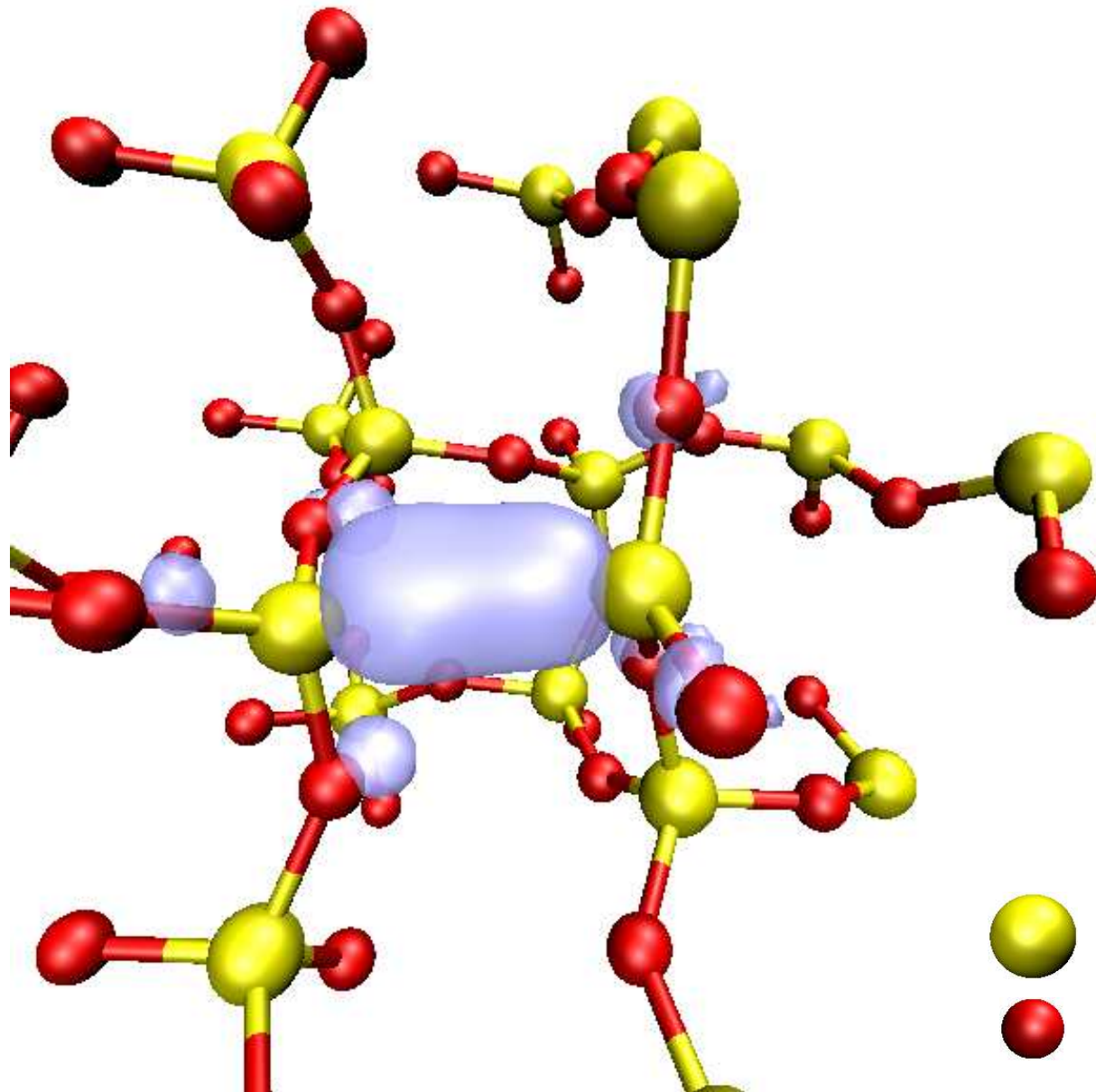
Density functional calculations (DFT) of  $E'$  center 'charging & puckering'





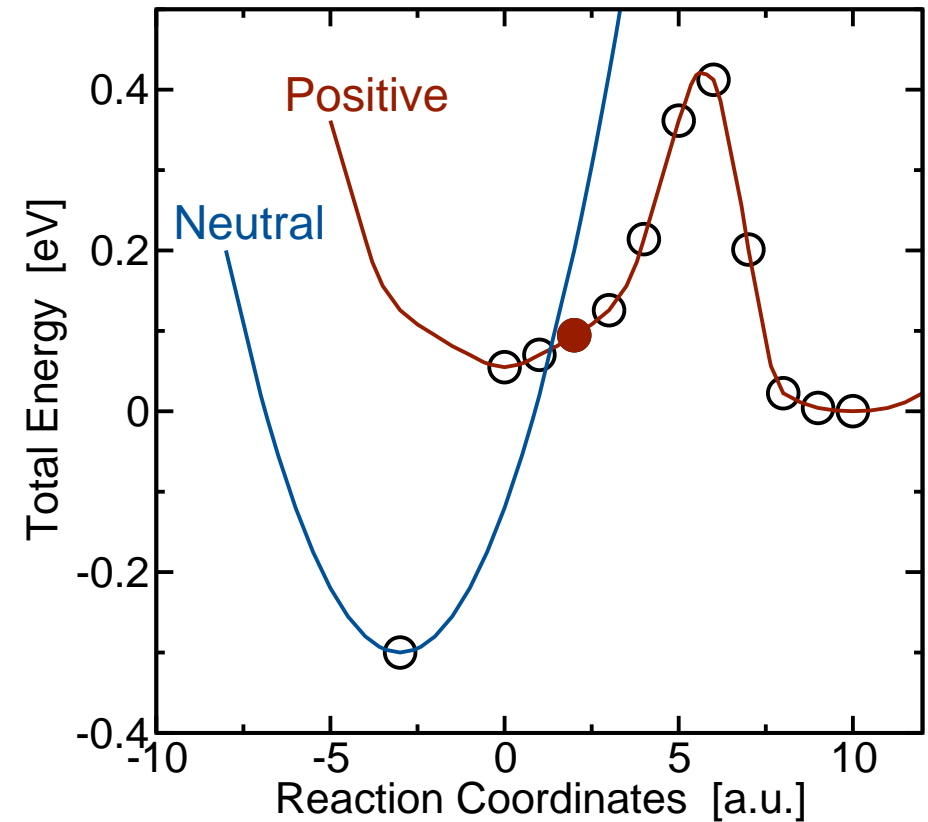
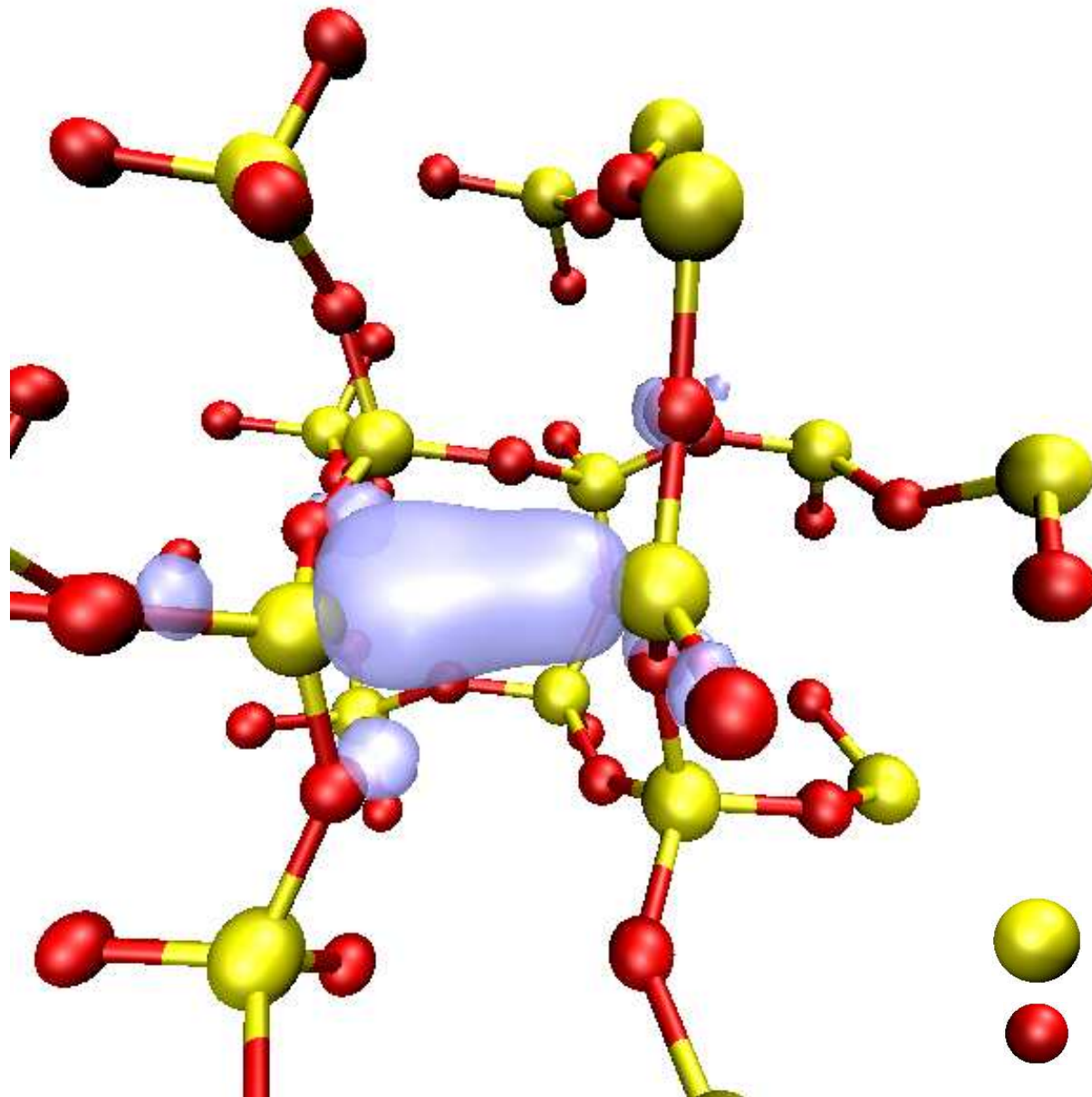
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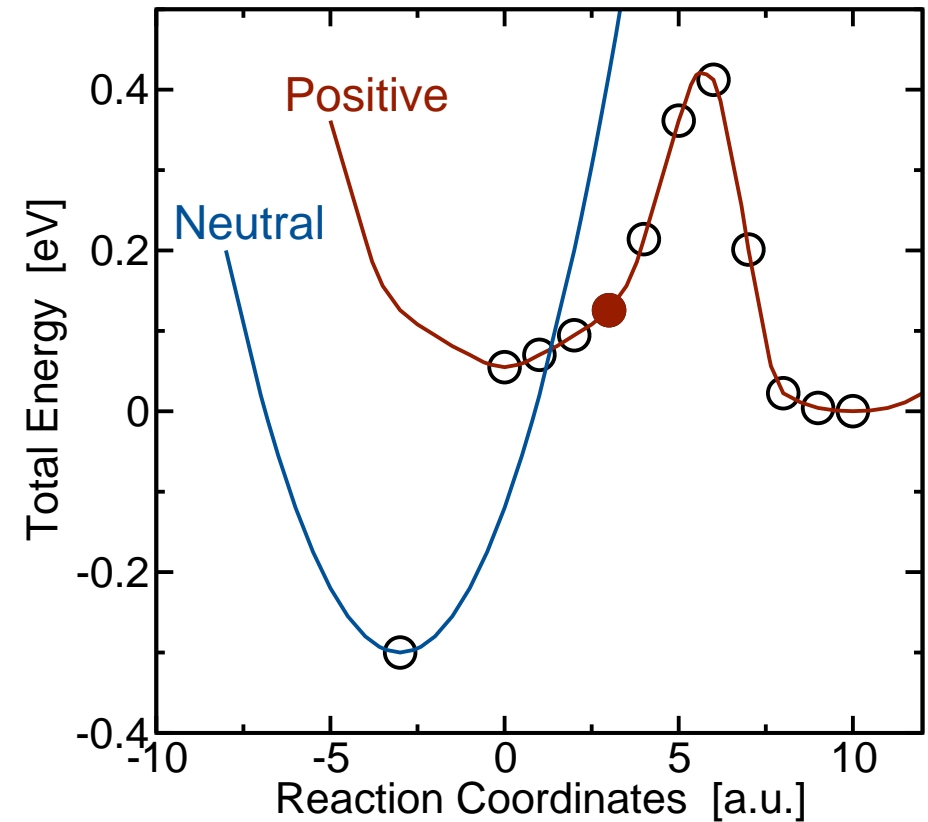
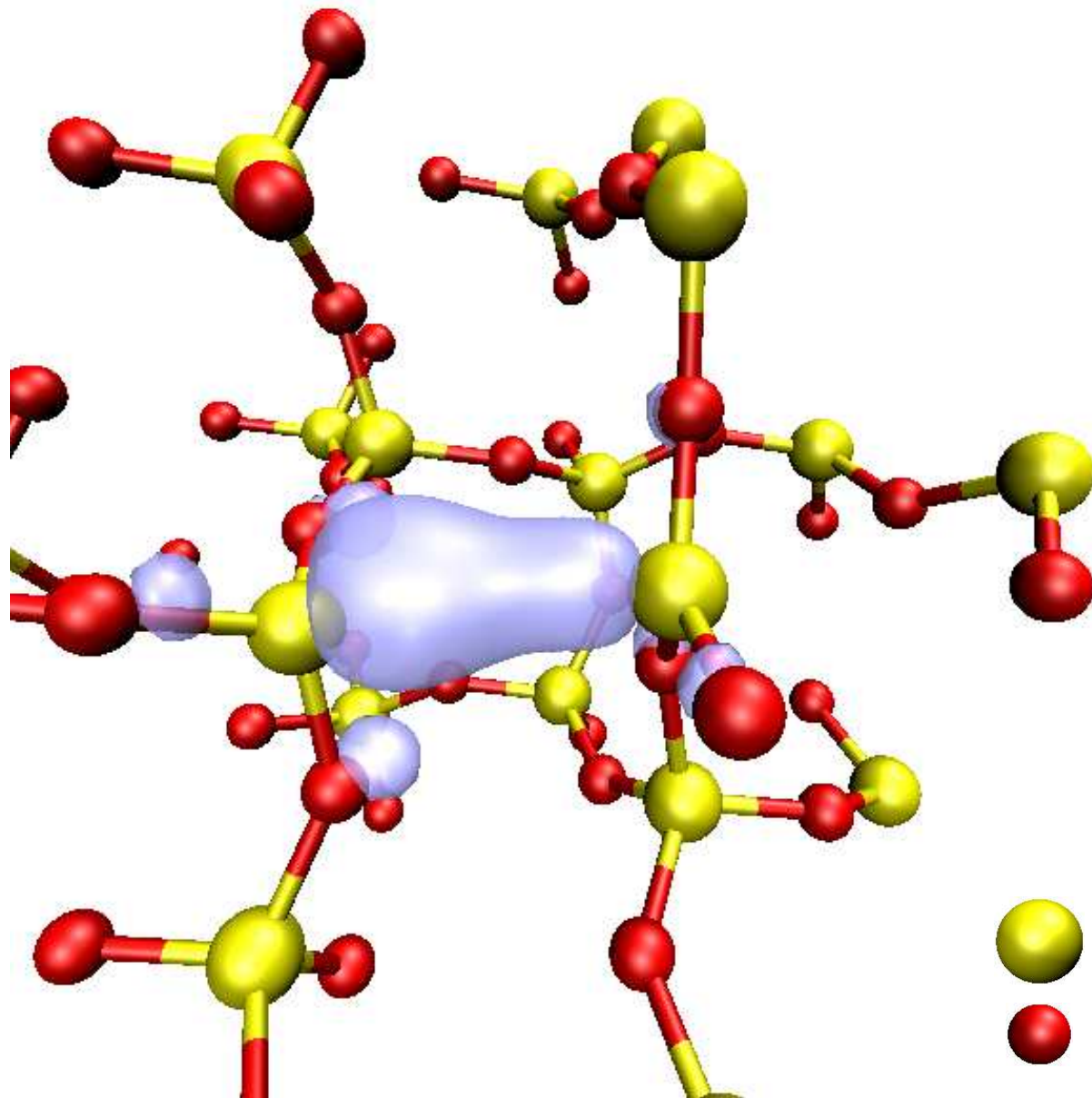
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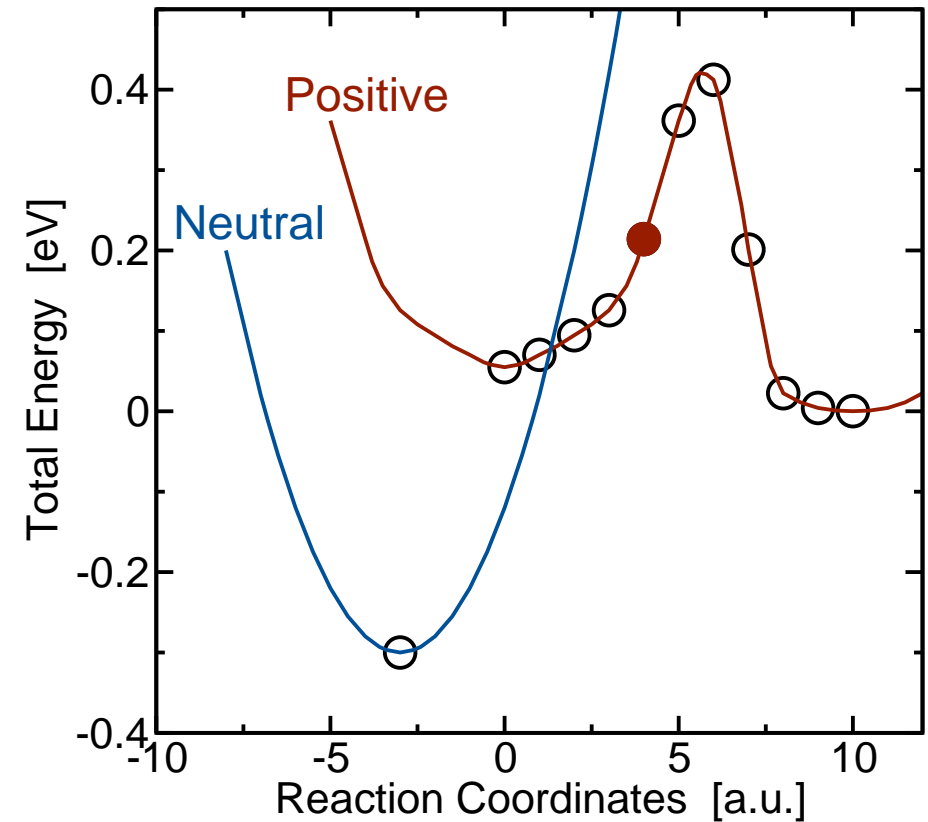
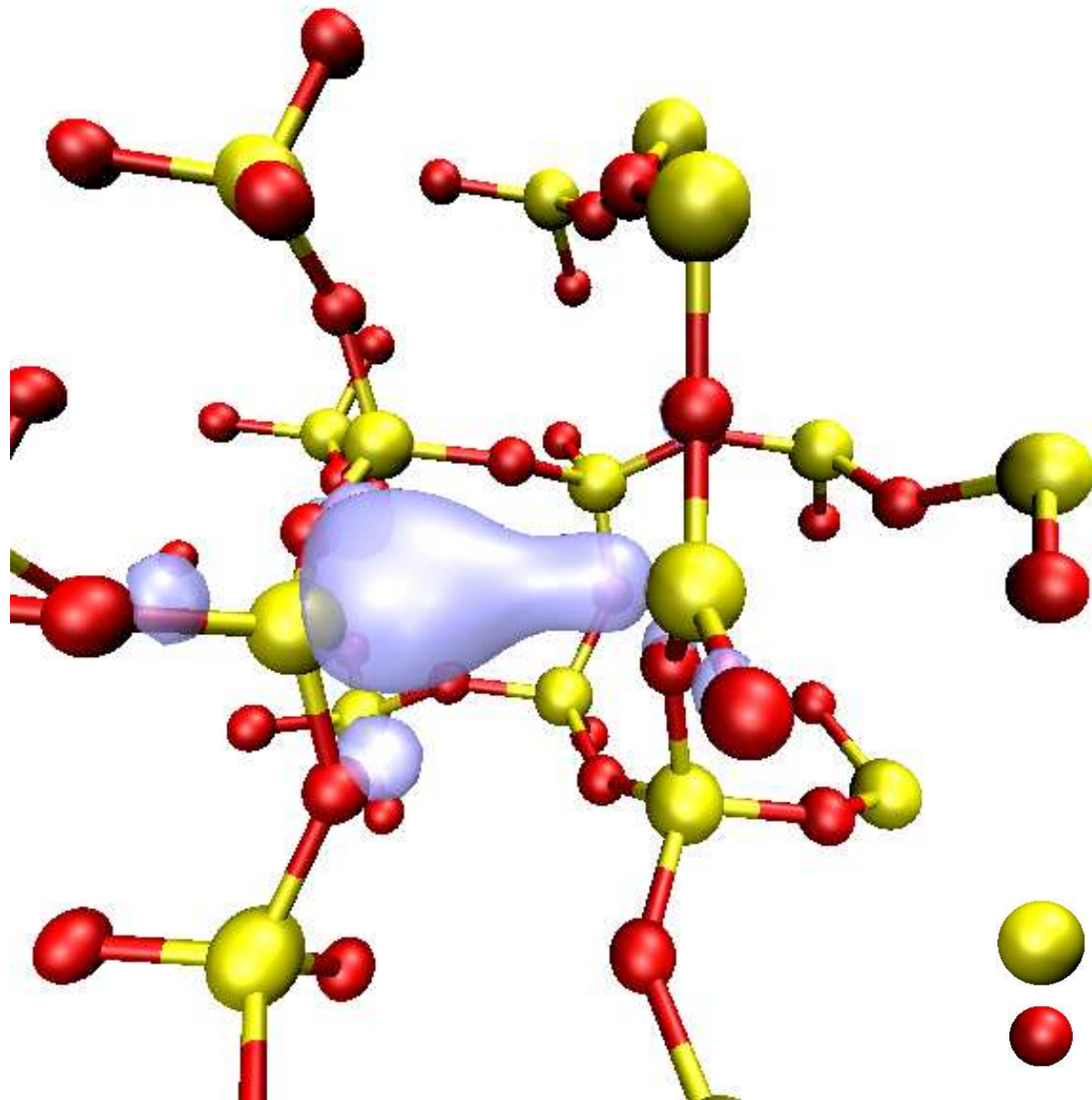
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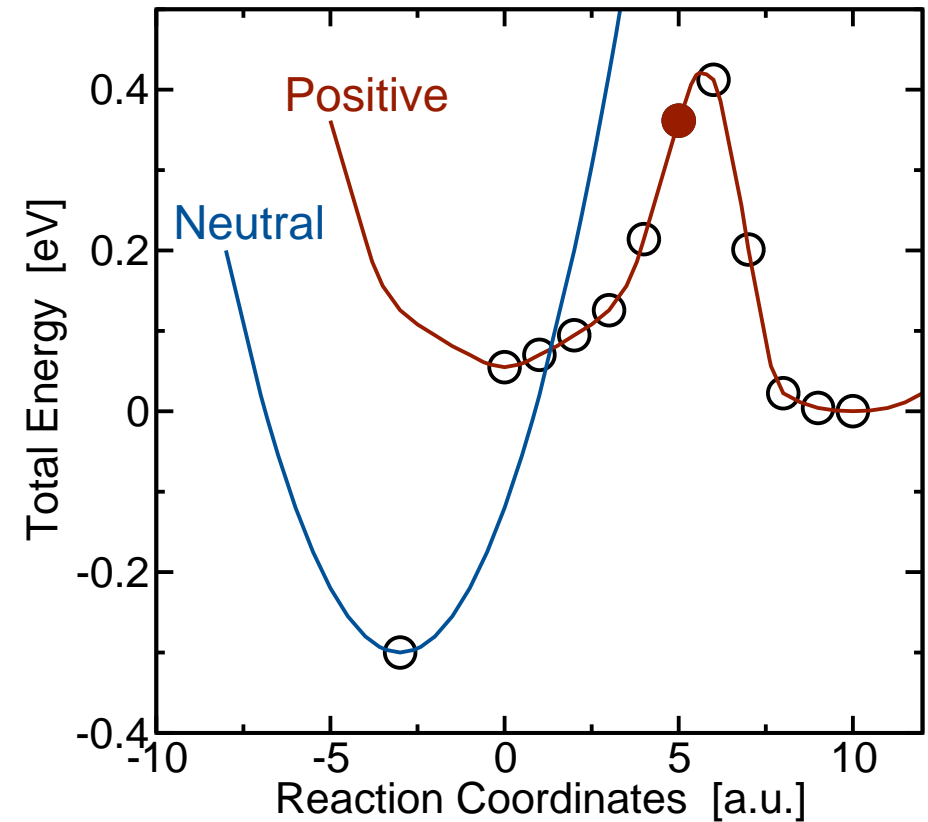
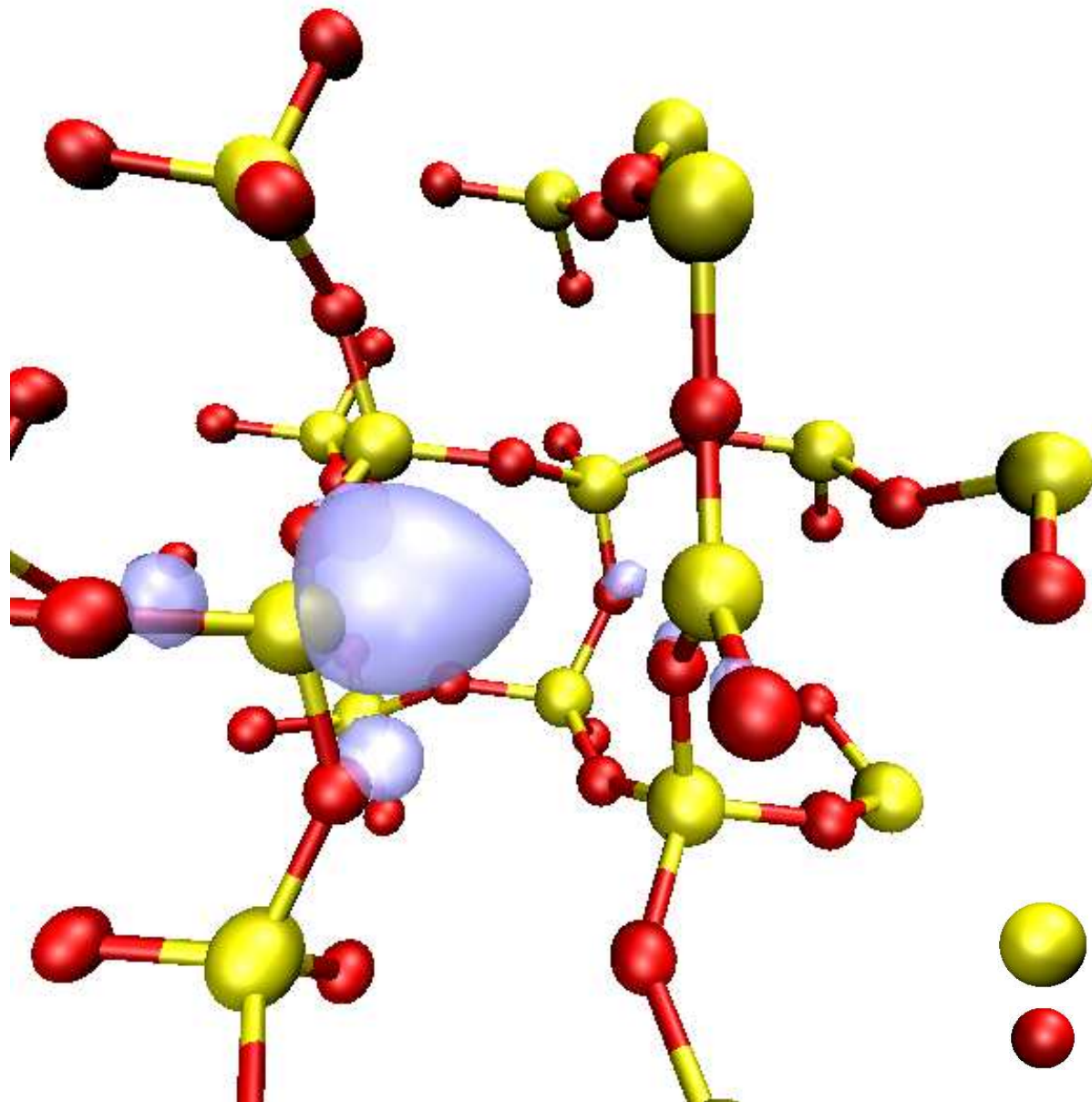
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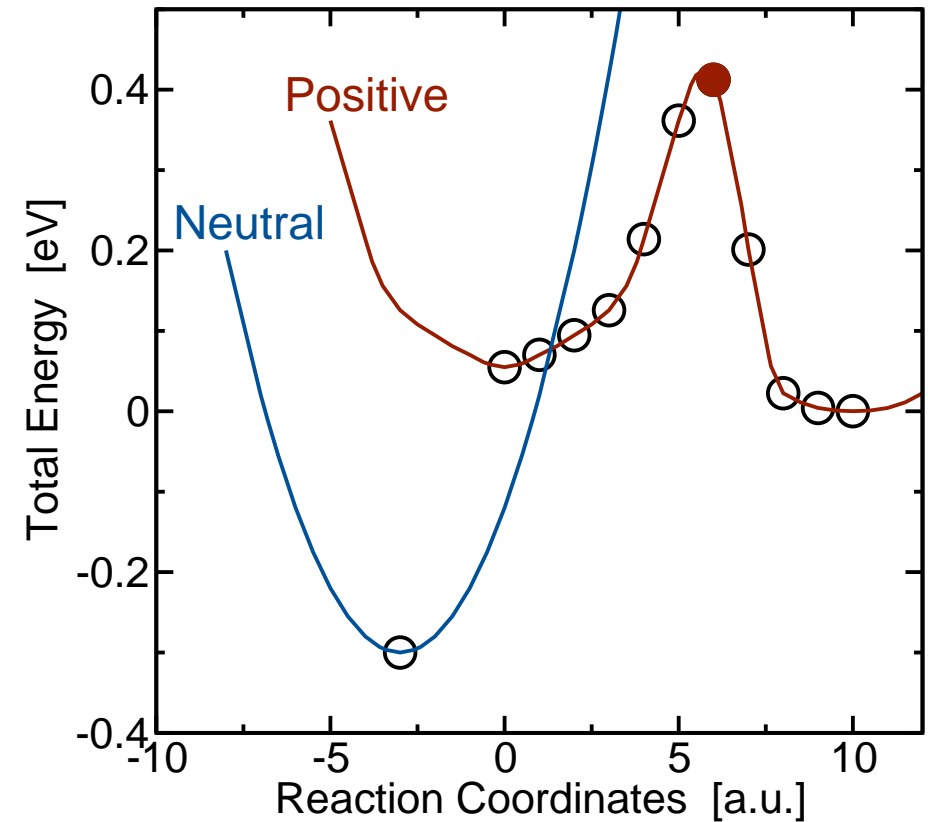
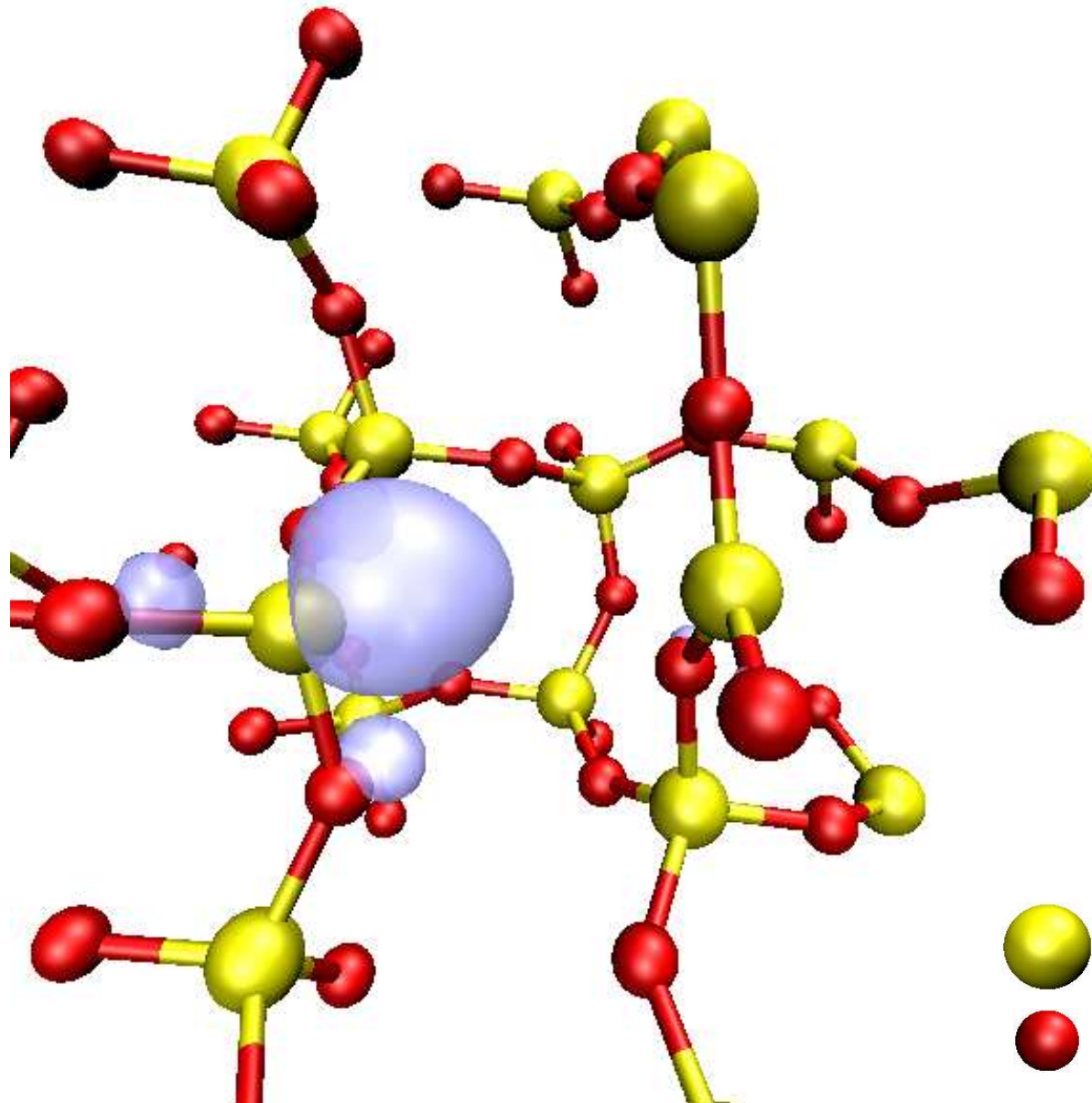
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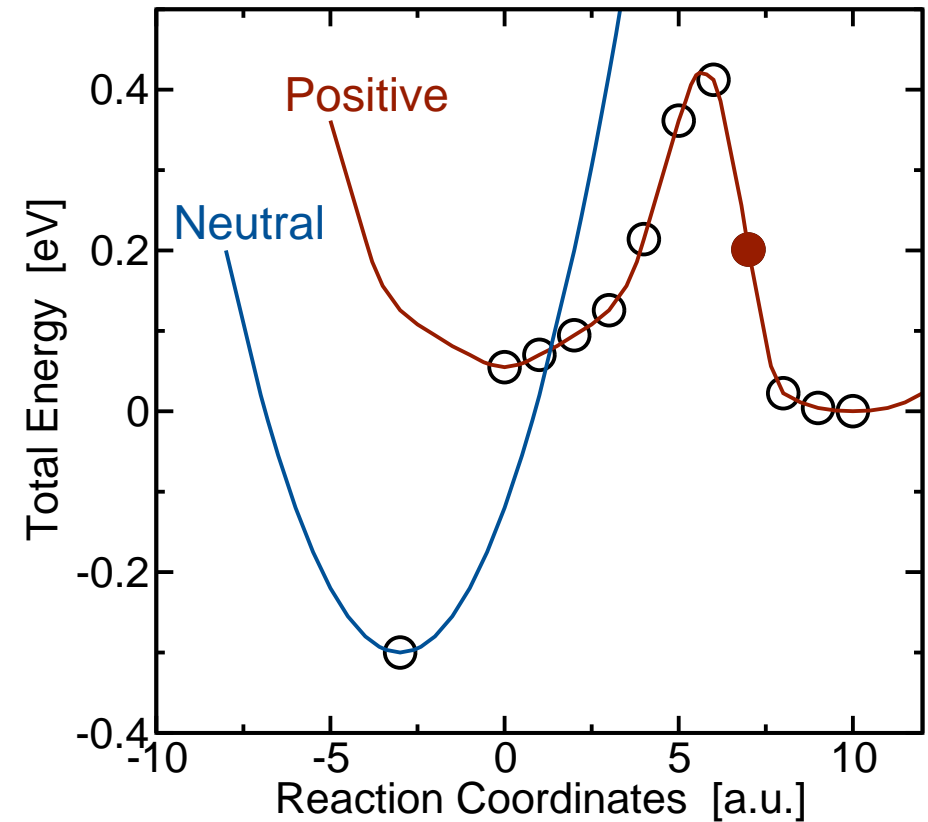
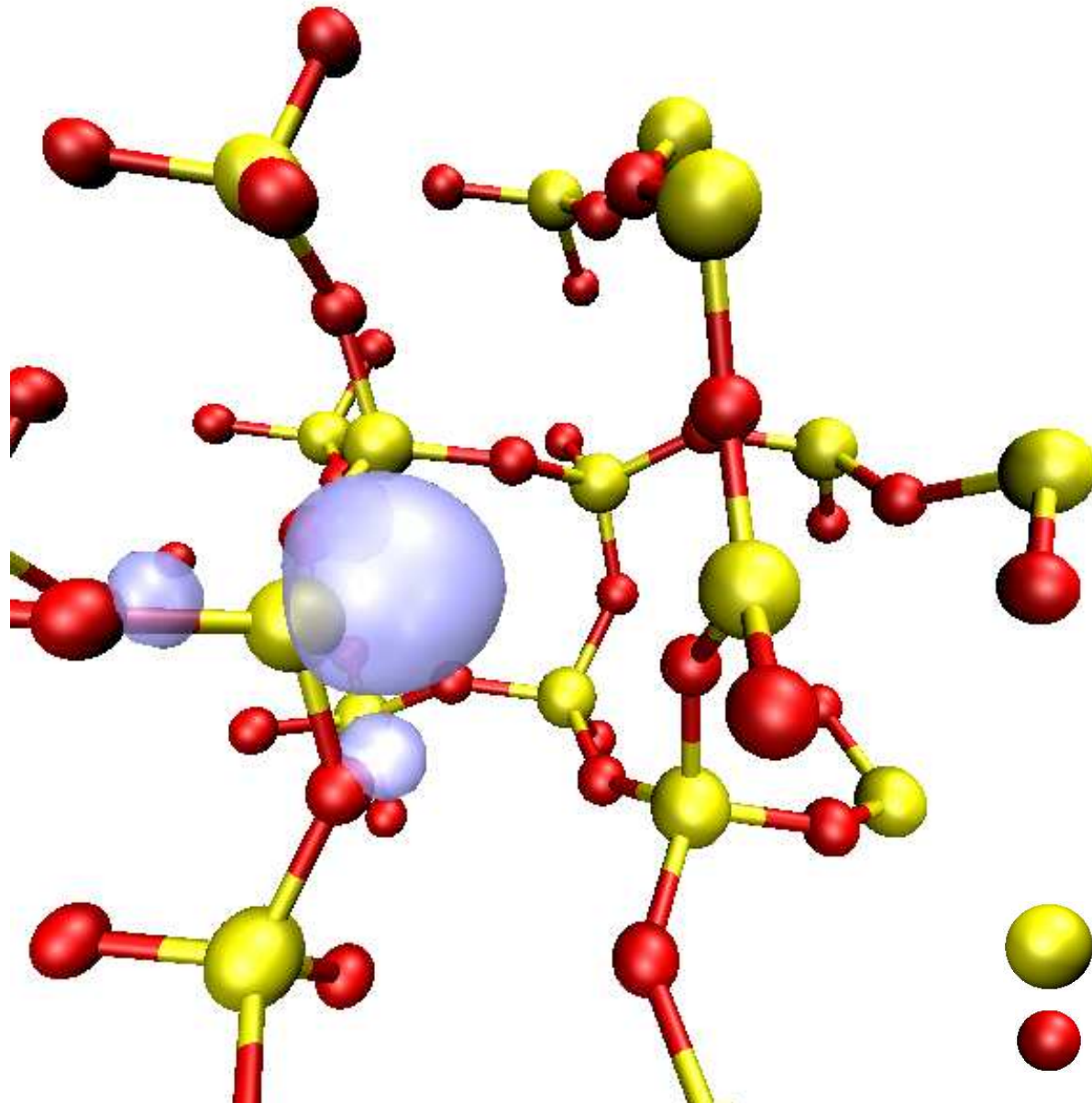
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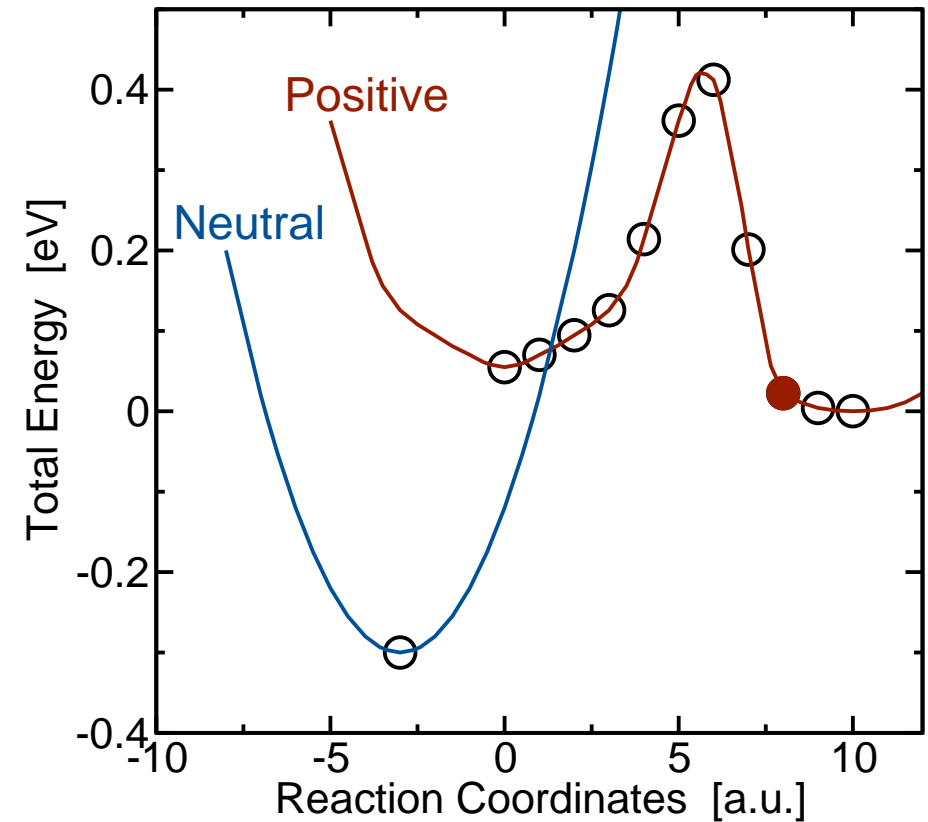
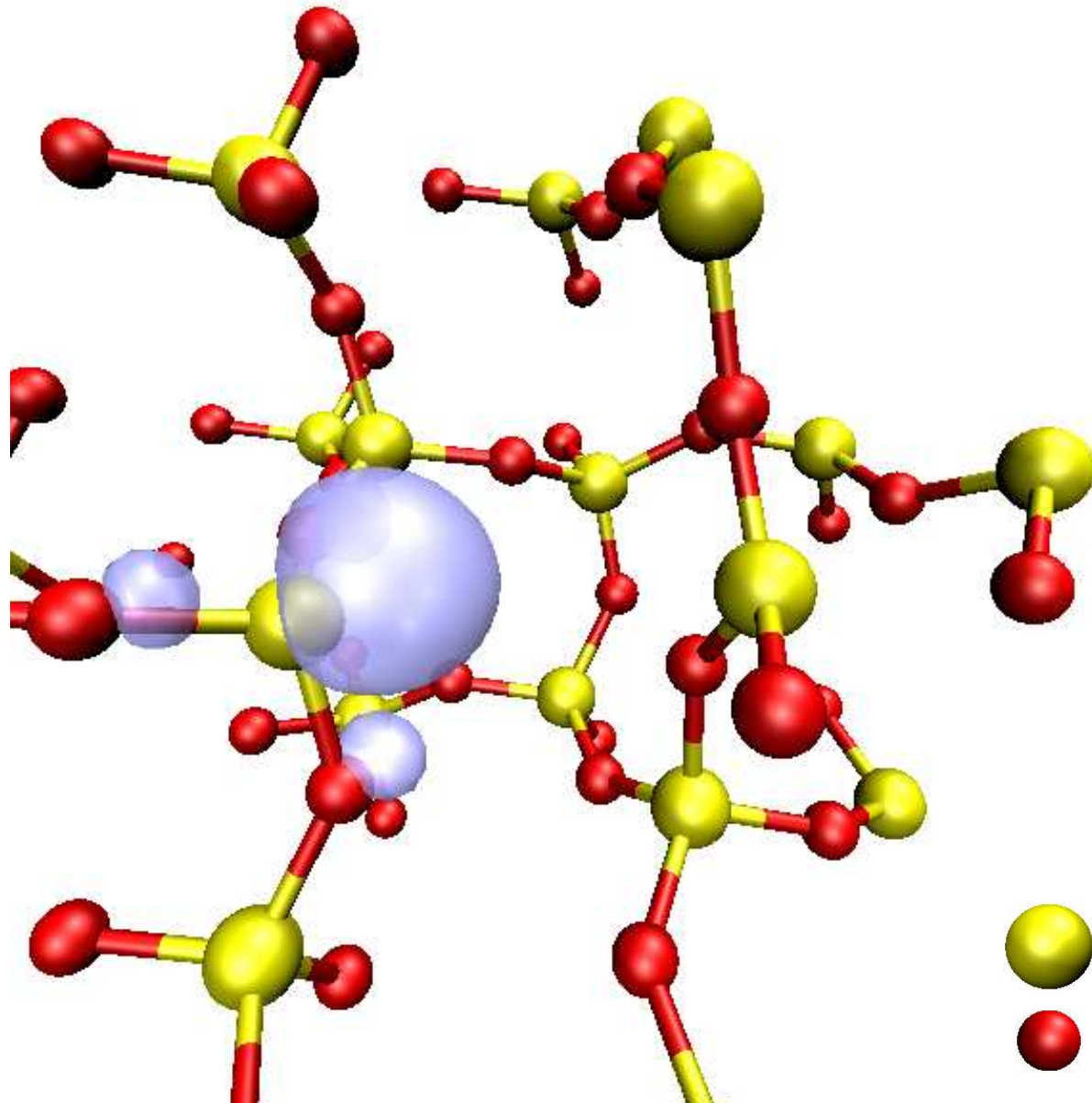
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# Lattice Relaxation and Metastability

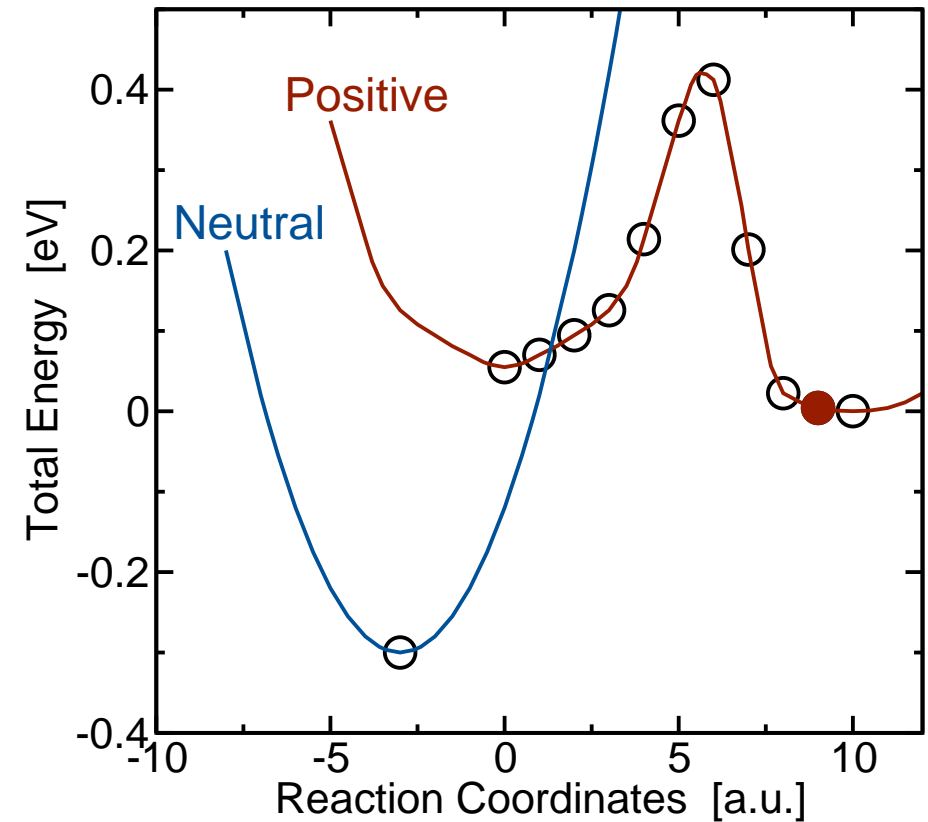
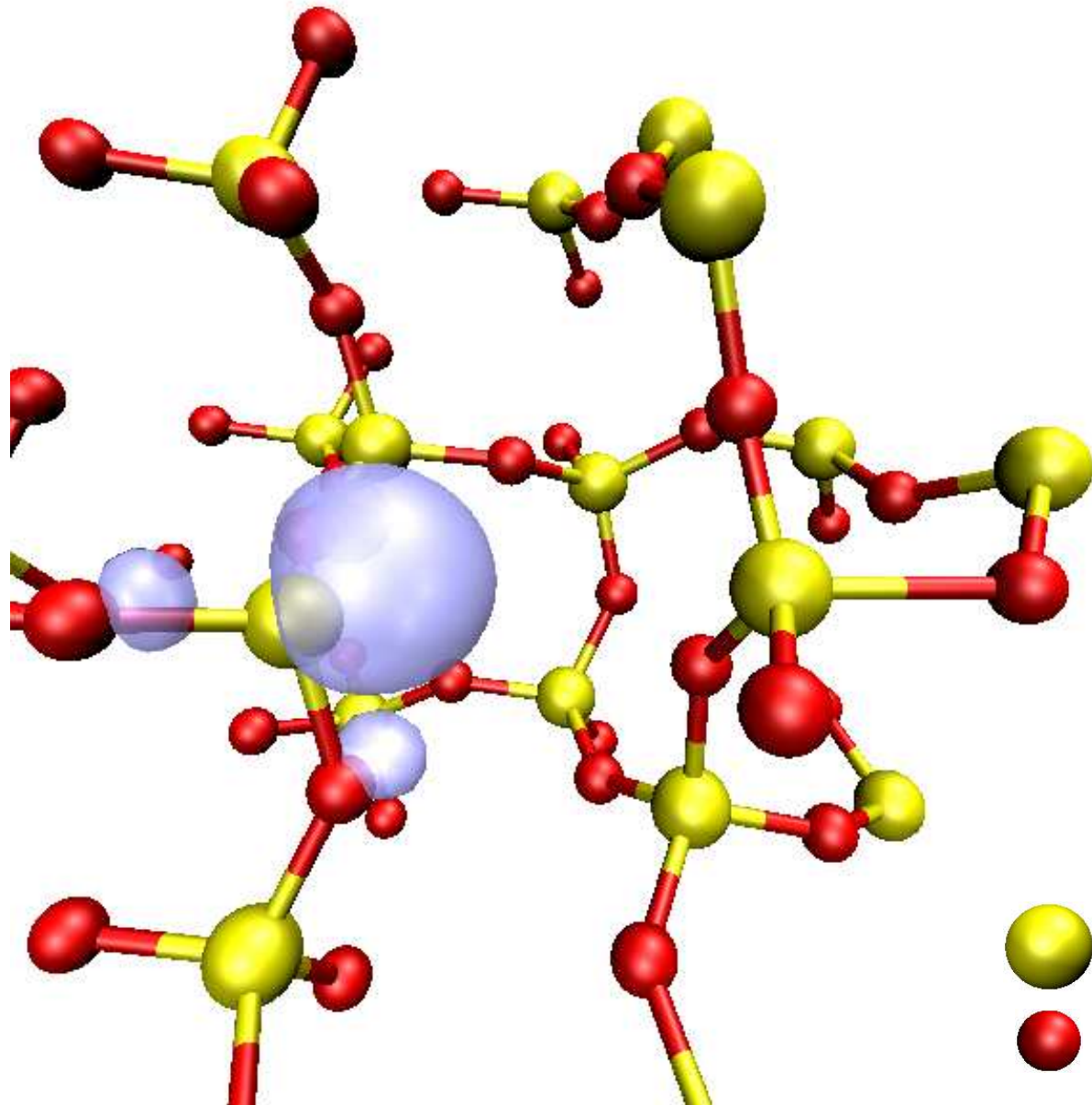
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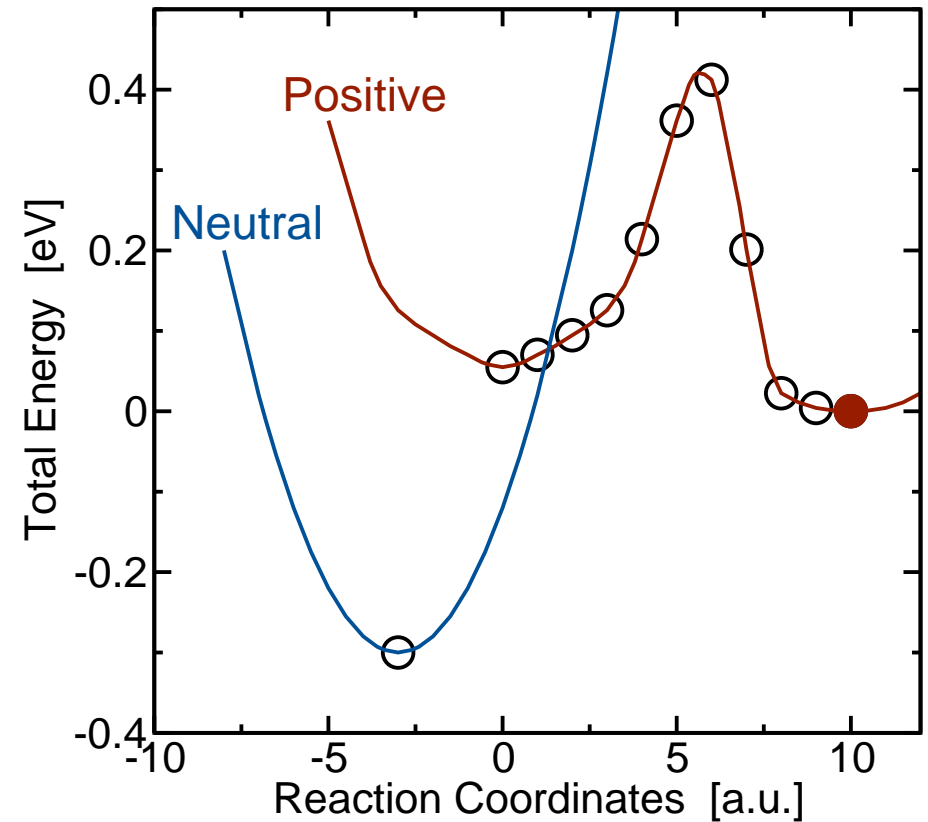
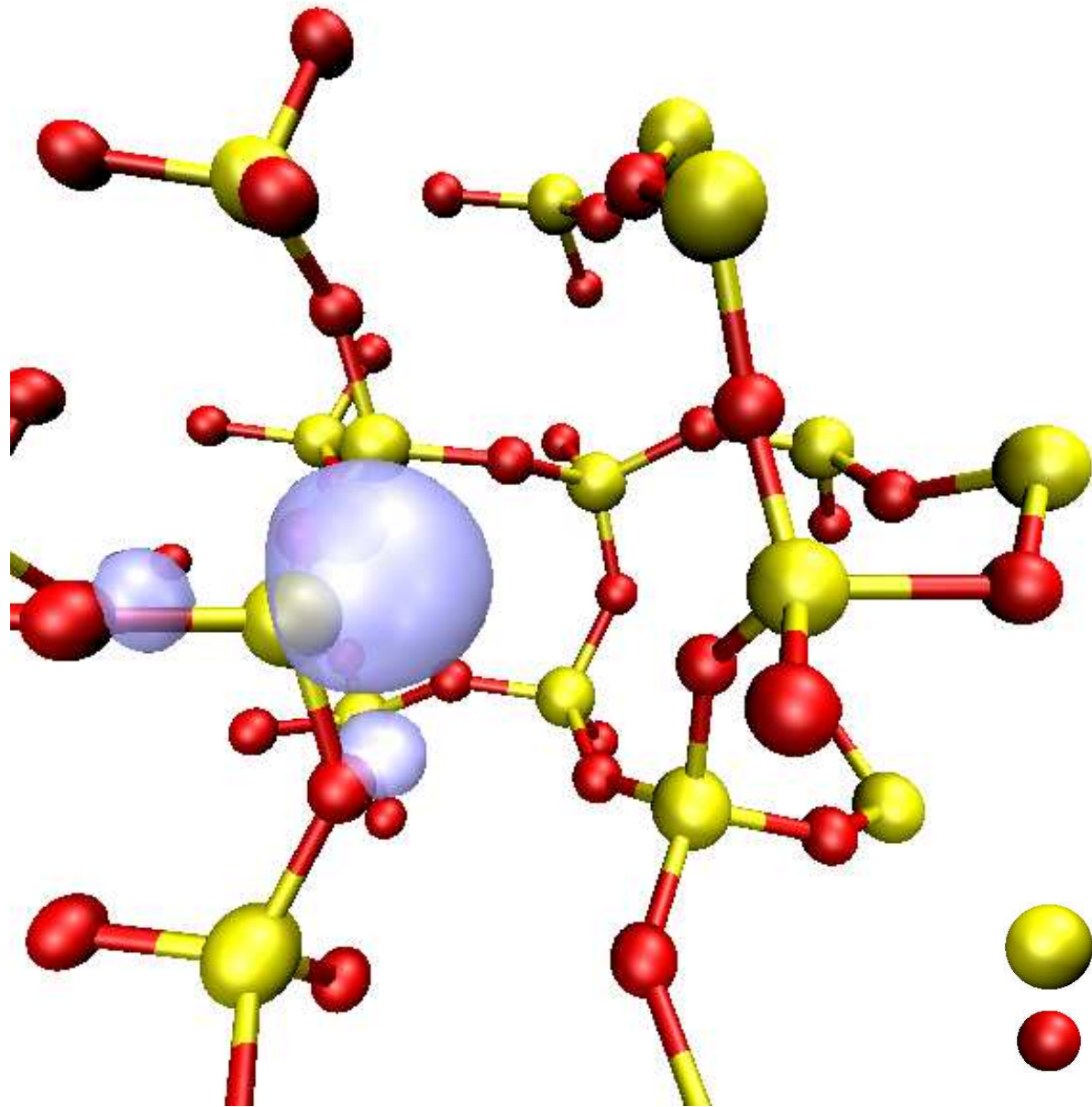
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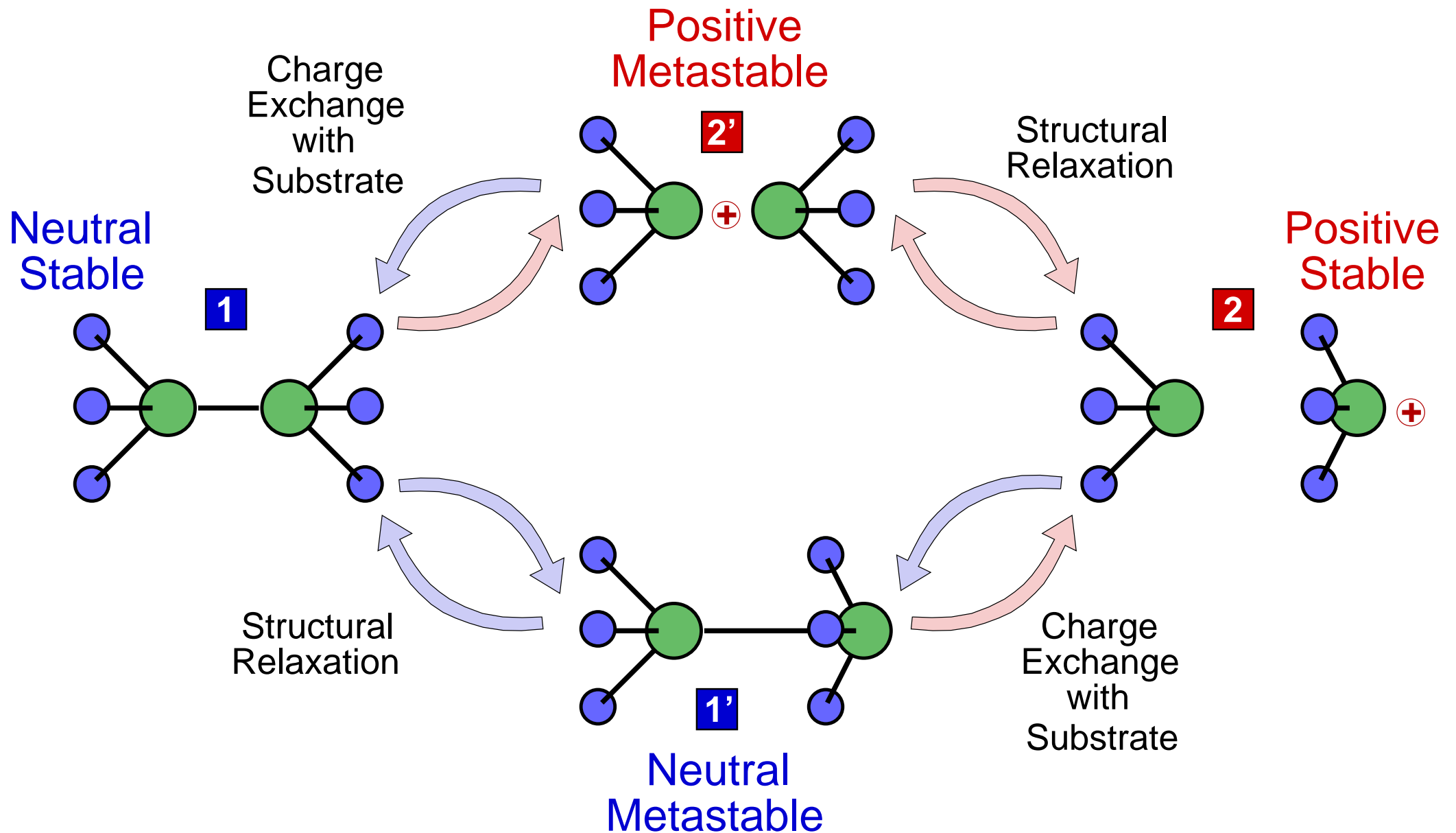
# Lattice Relaxation and Metastability

Density functional calculations (DFT) of  $E'$  center 'charging & puckering'



- Silicon
- Oxygen

# Detailed Defect Model Required



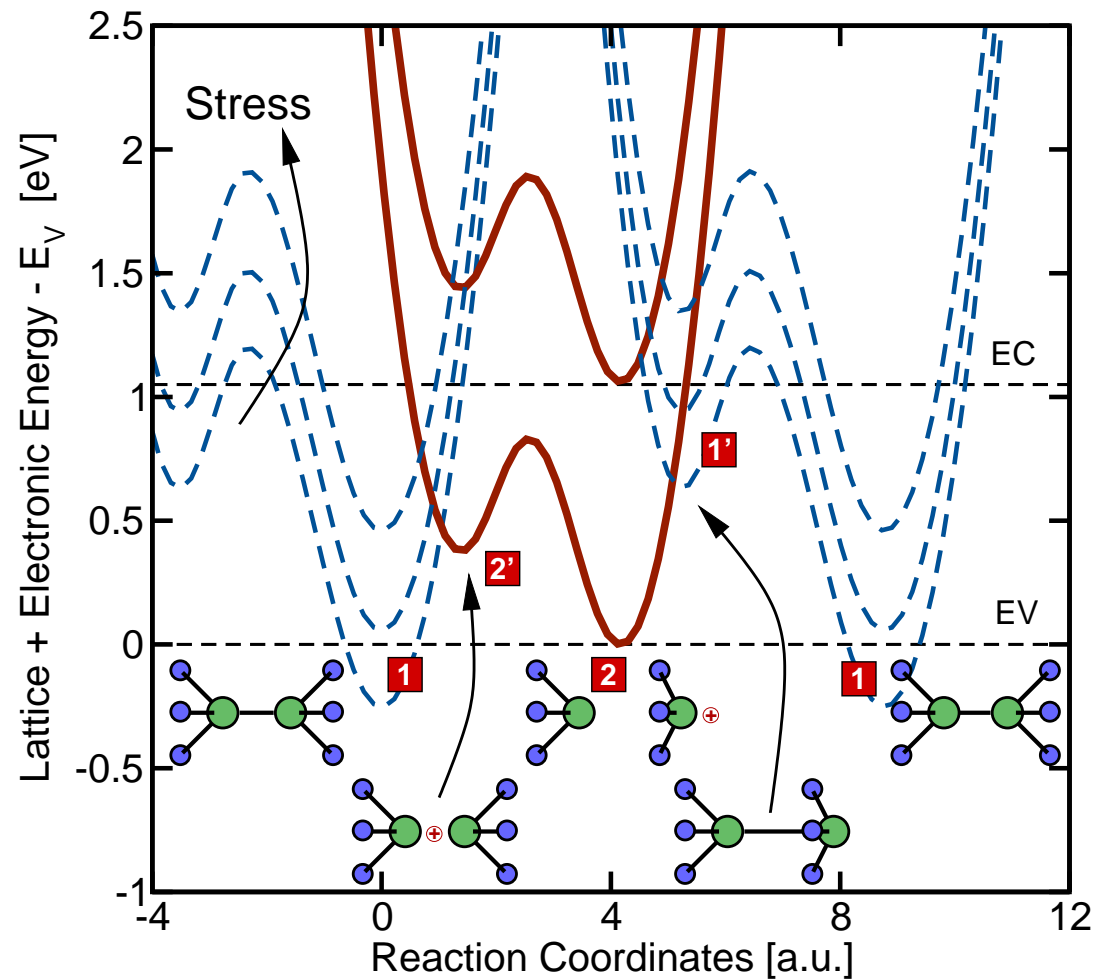
# Model

Different adiabatic potentials for the neutral and positive defect

Metastable states 2' and 1' are secondary minima

Thermal transitions to ground states 1 and 2

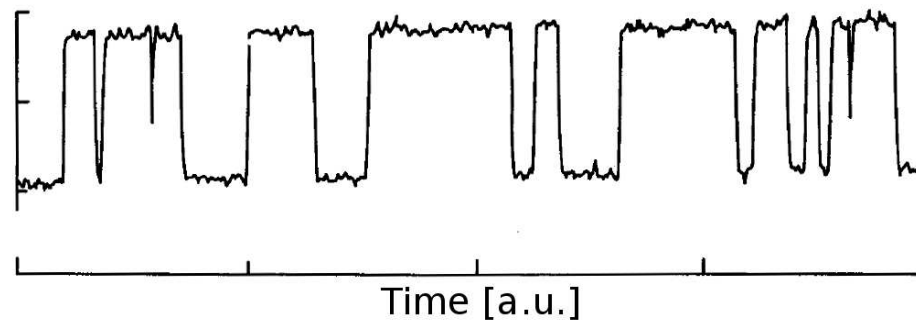
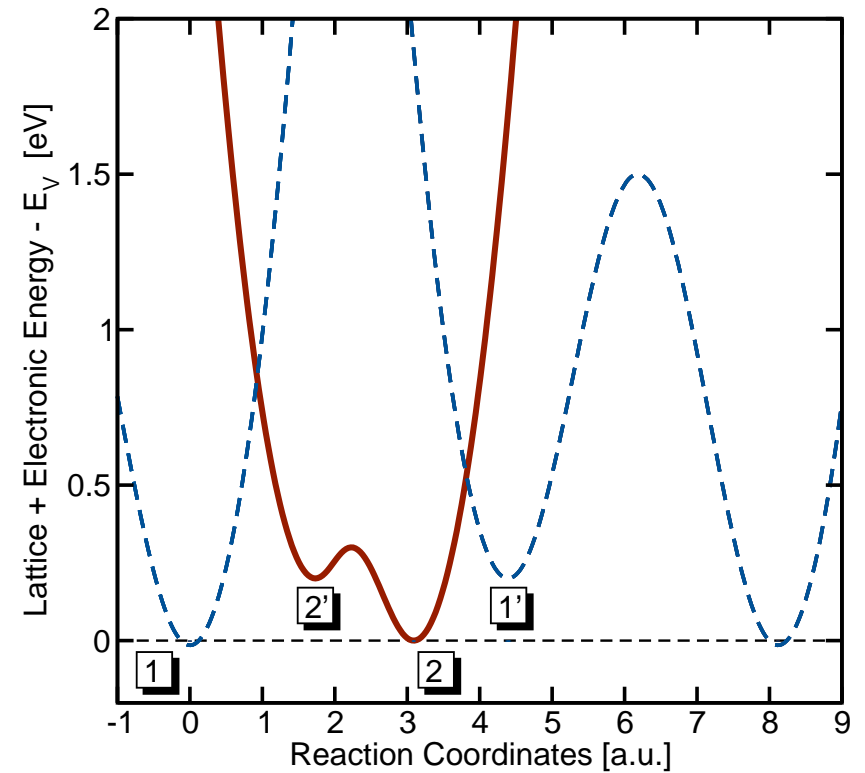
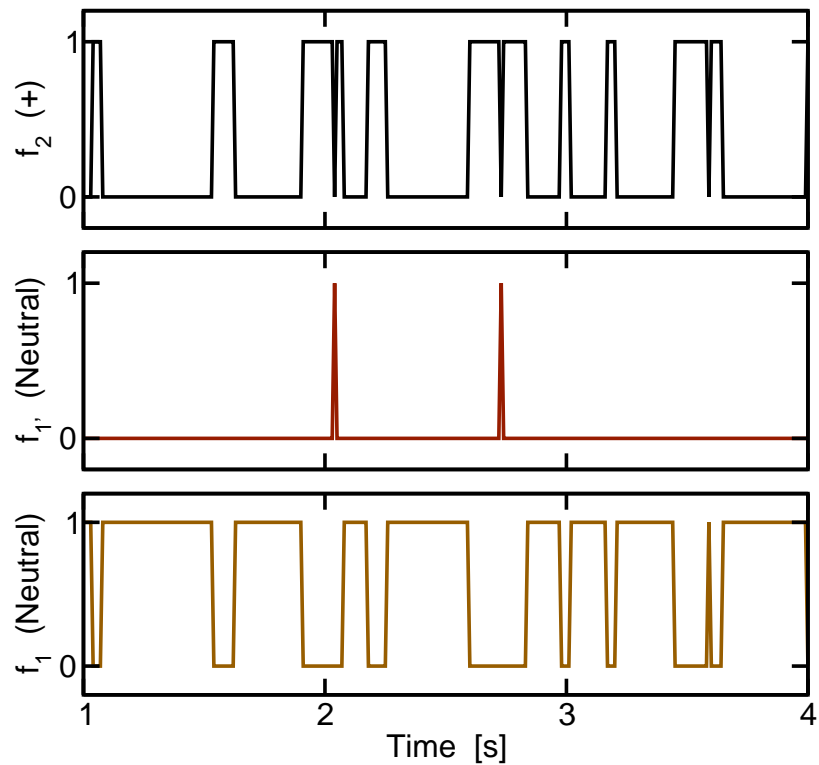
Stochastic Markov-model for defect kinetics based on multiphonon theory



# Qualitative Model Evaluation

## Normal random telegraph noise (RTN)

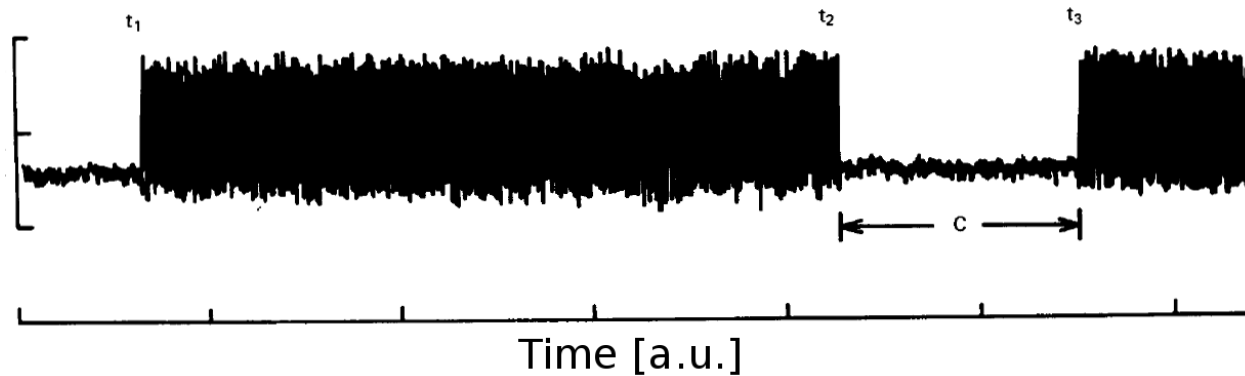
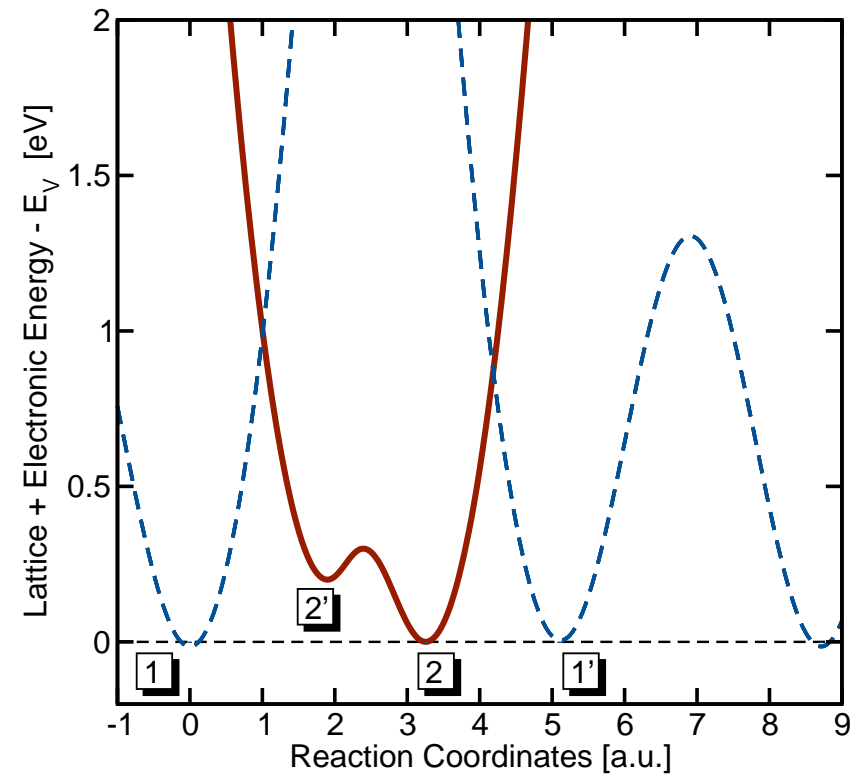
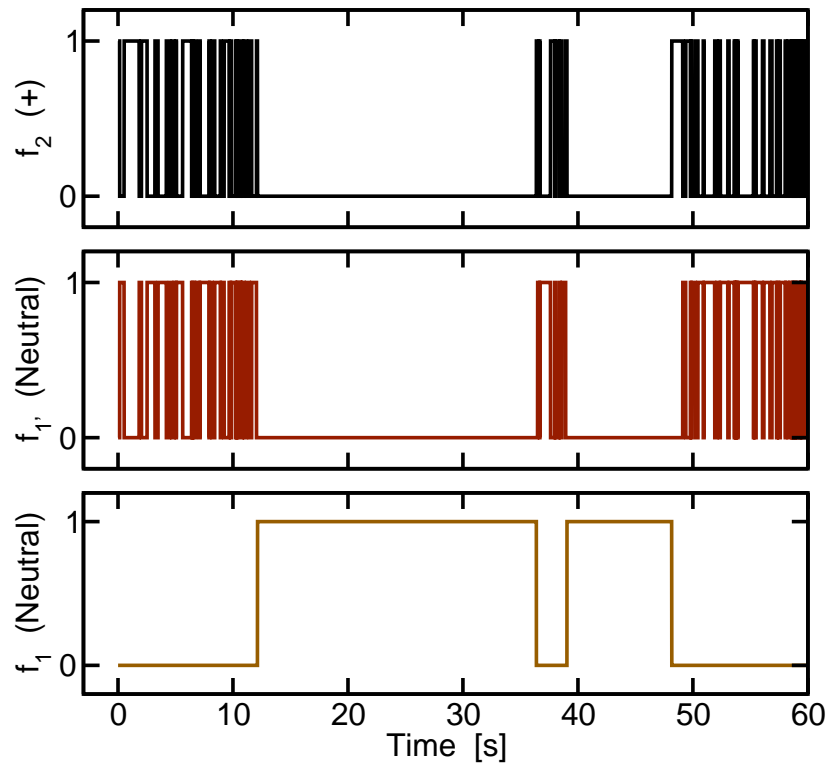
Very similar energetical position of the minimas 1 and 2



# Qualitative Model Evaluation

## Anomalous RTN

Very similar energetical position of the three minima 1, 2, and 1'

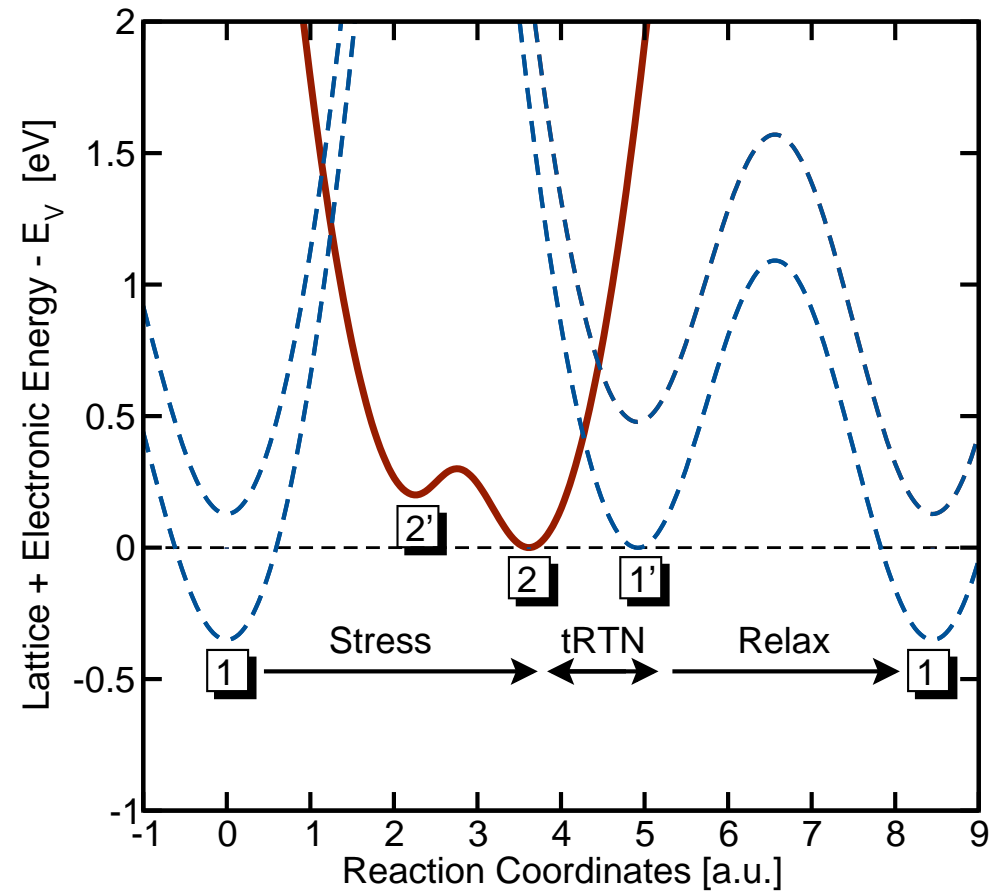
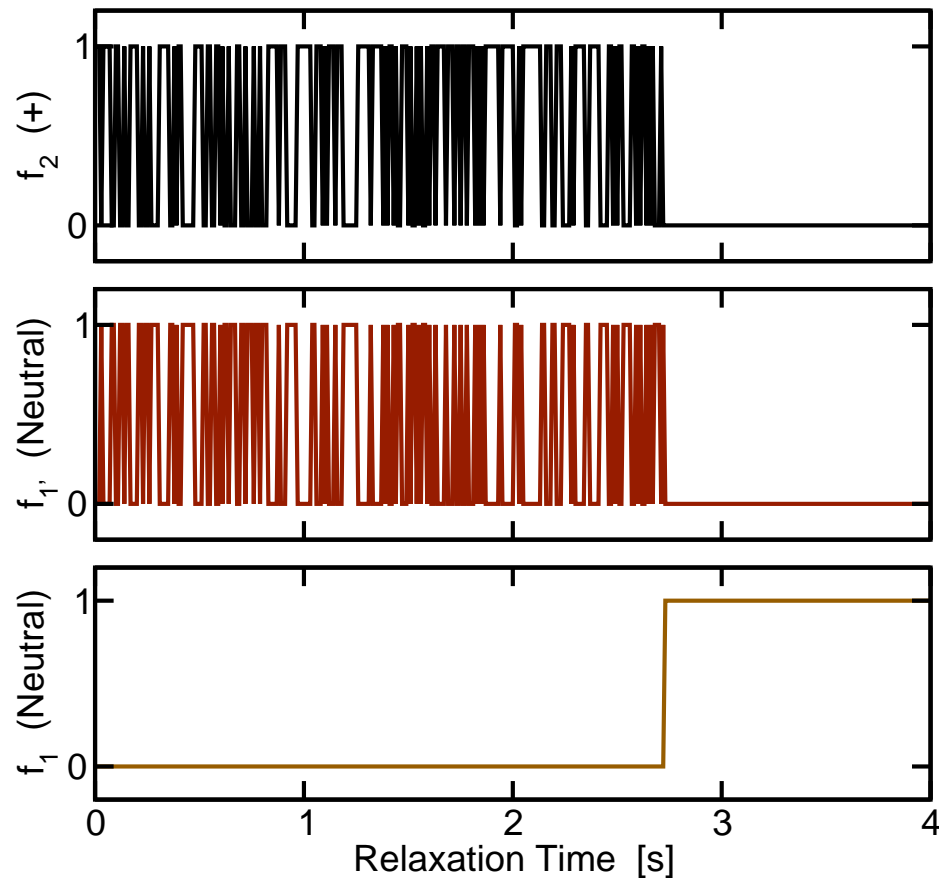


Uren *et al.*, PRB '88

# Qualitative Model Evaluation

## Temporary random telegraph noise (tRTN)

Very similar energetical position of the minima 2 and 1'



# Quantitative Model Evaluation

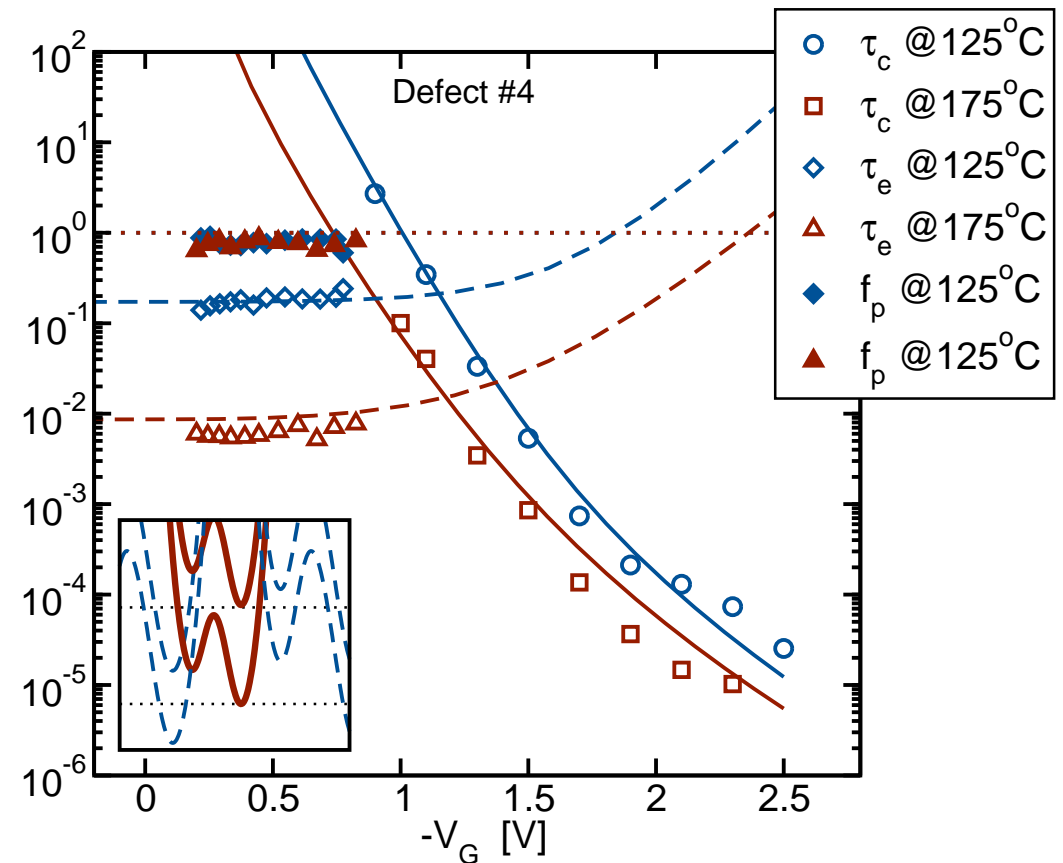
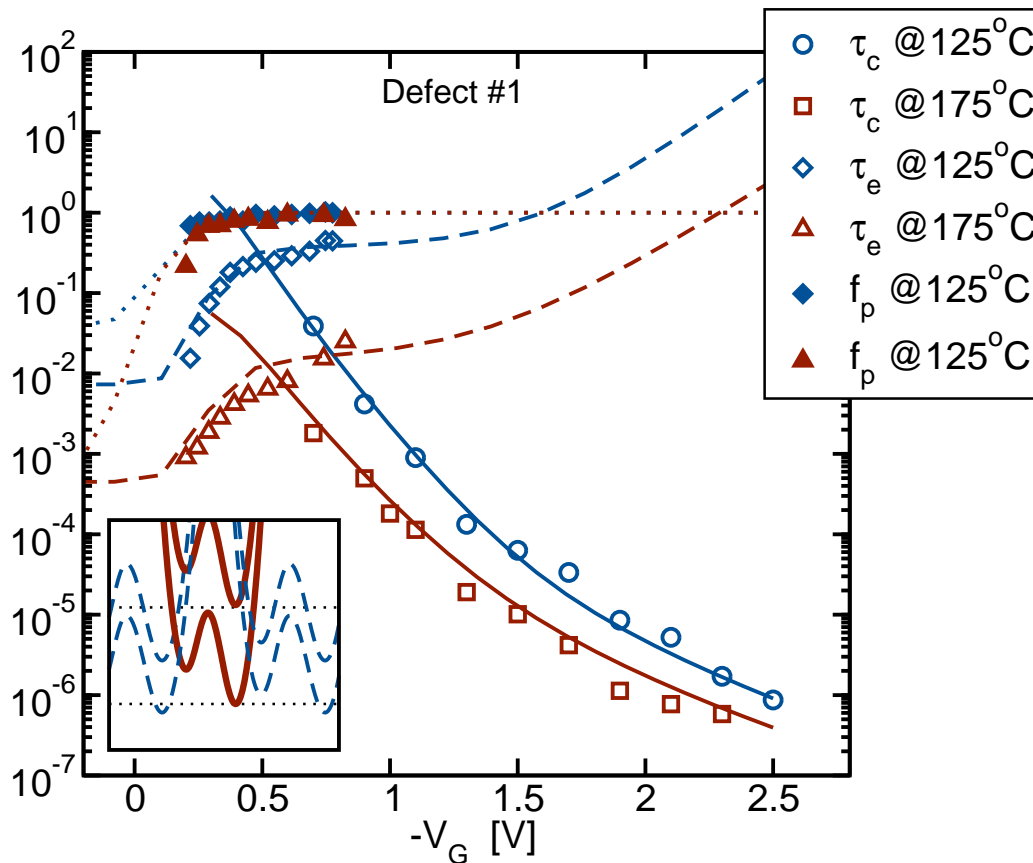
Excellent agreement for both capture and emission time constants

Capture time: particularly important for back-extrapolation of stress data

Emission time: determines recovery behavior

Does the defect act like a switching trap?

Depends on the defect configuration

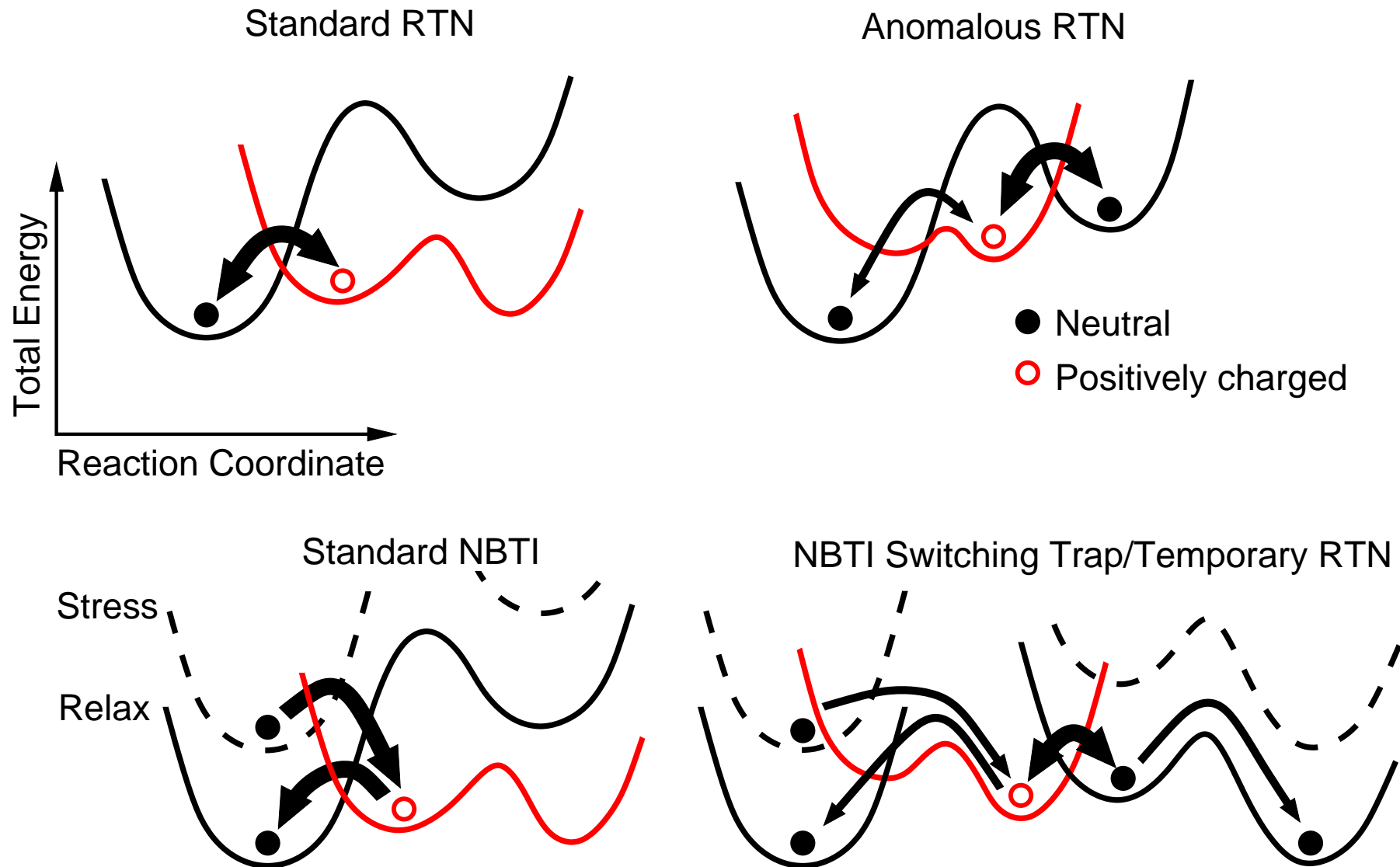




# Model Summary

All features can be consistently explained with a general defect model

Differences simple consequences of defect potentials (amorphous oxide!)



# How to Determine the Lifetime?

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Small area devices: lifetime is a stochastic quantity

For details please refer to: Grasser *et al.* IEDM '10.

# Conclusions

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Statistics of individual defects become important in nanoscale MOSFETs

- Random number of traps

- Random distribution of traps in space

- Random defect properties

- Interaction with random discrete dopants

- Discrete stochastic charge capture and emission events

Measurement method: time dependent defect spectroscopy (TDDS)

- Allows extraction of  $\bar{\tau}_e$ ,  $\bar{\tau}_c$ , and step-height over very wide range

- Allows simultaneous analysis of multiple defects

New defect model

- Metastable defect states, nonradiative multiphonon theory, stochastic behavior

Fundamental implications on device reliability

- Lifetime is a stochastic quantity

- Lifetime will have a huge variance